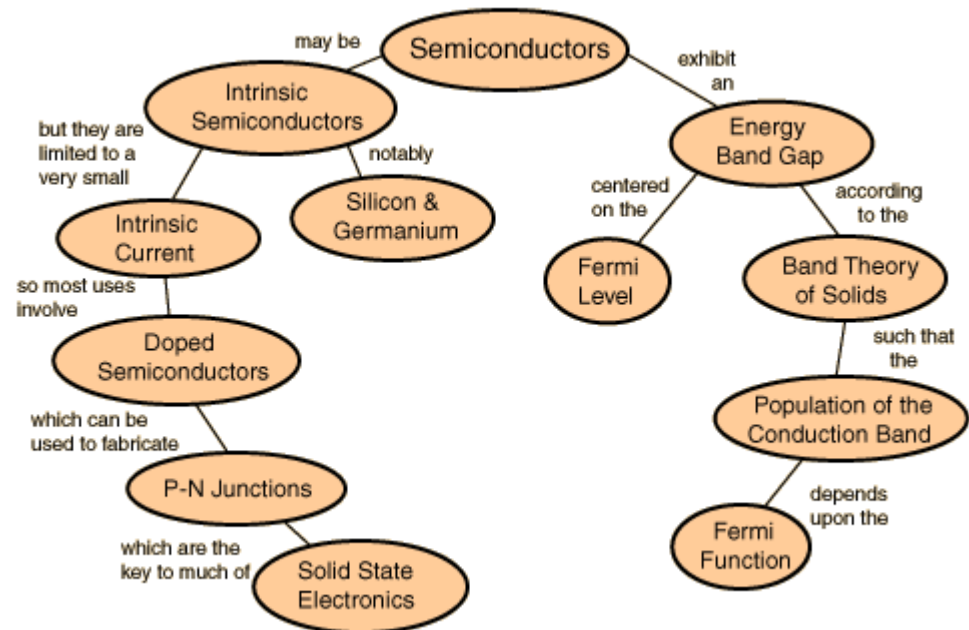


Semiconductors – a brief introduction

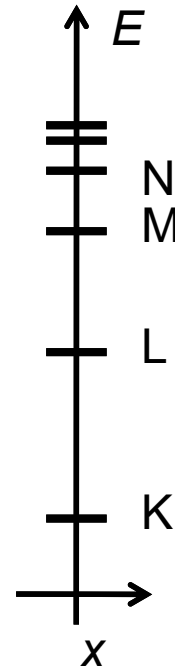
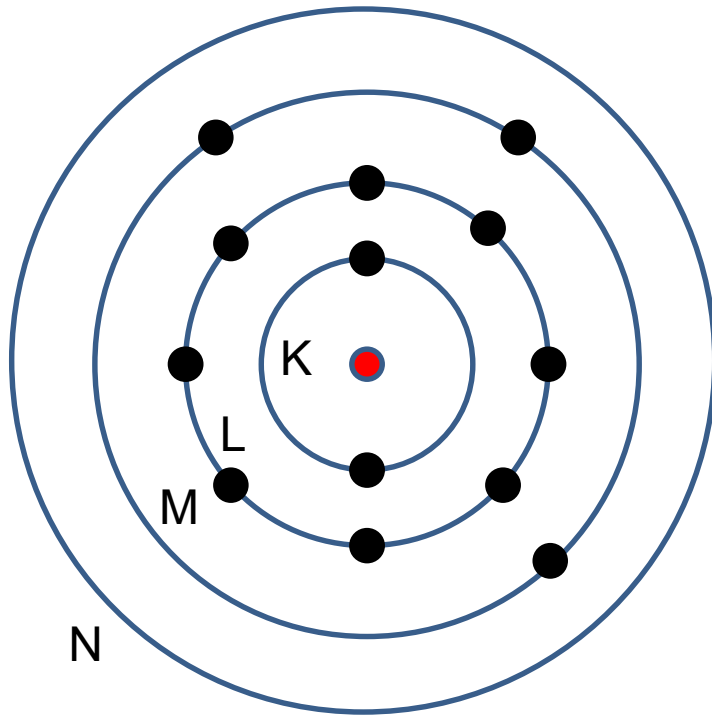
- Band structure – from atom to crystal
- Fermi level – carrier concentration
- Doping
- Transport (drift-diffusion)

Reading: (Sedra/Smith 7th edition)
1.7-1.9

[Hyperphysics](#) (link on course homepage)
basic introduction to semiconductors
(almost no equations)

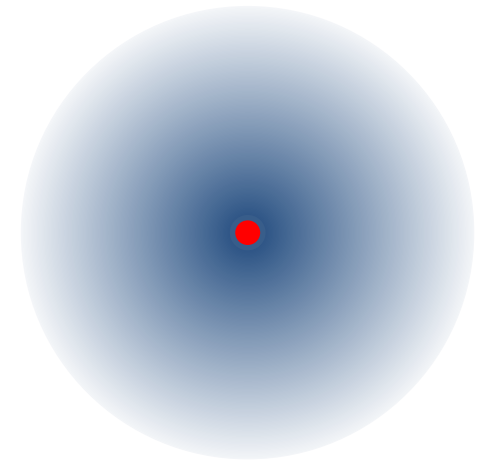


Atomic energy levels



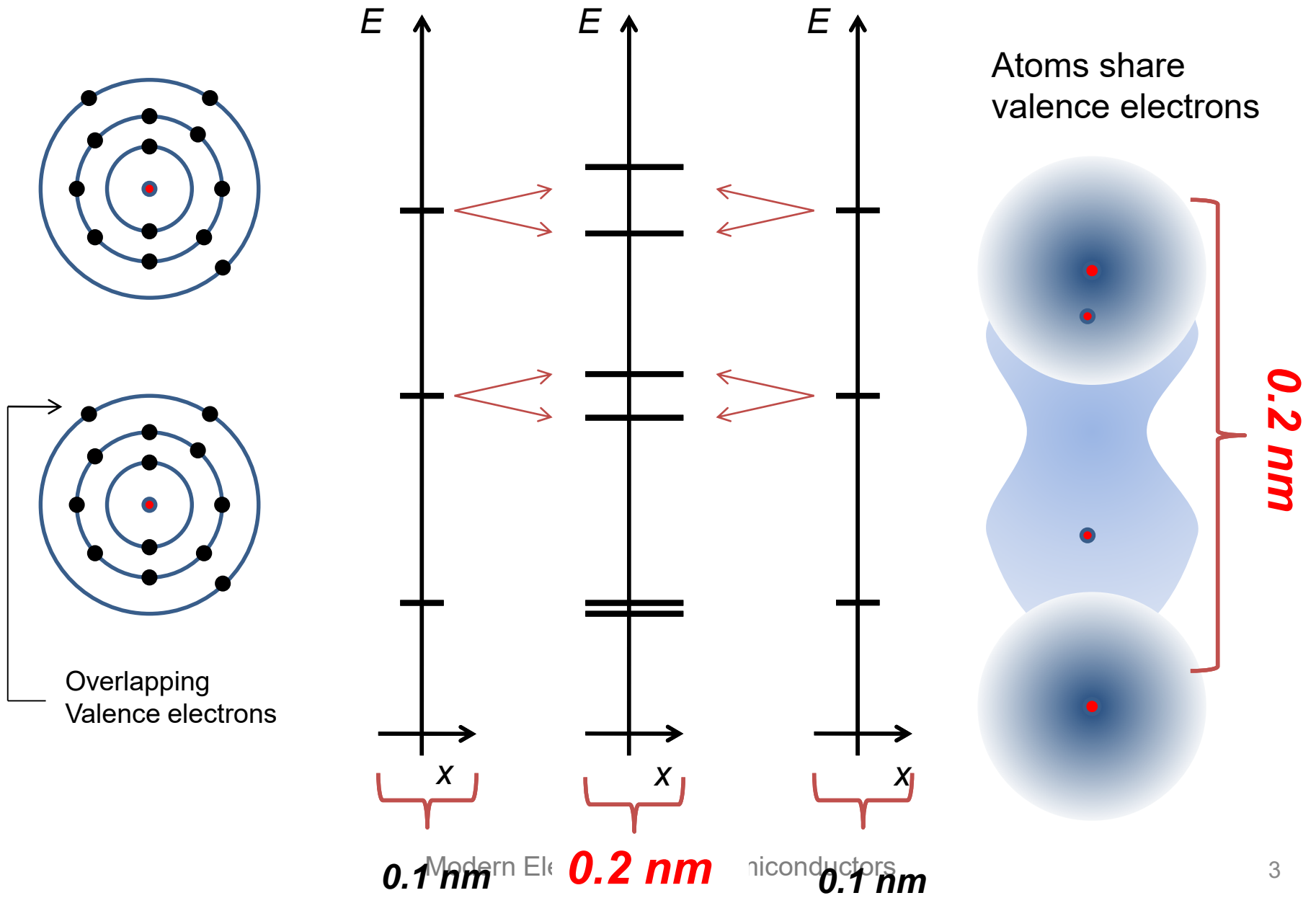
0.1 nm

Quantum mechanics:
Wavefunction gives describes
probability to find electron

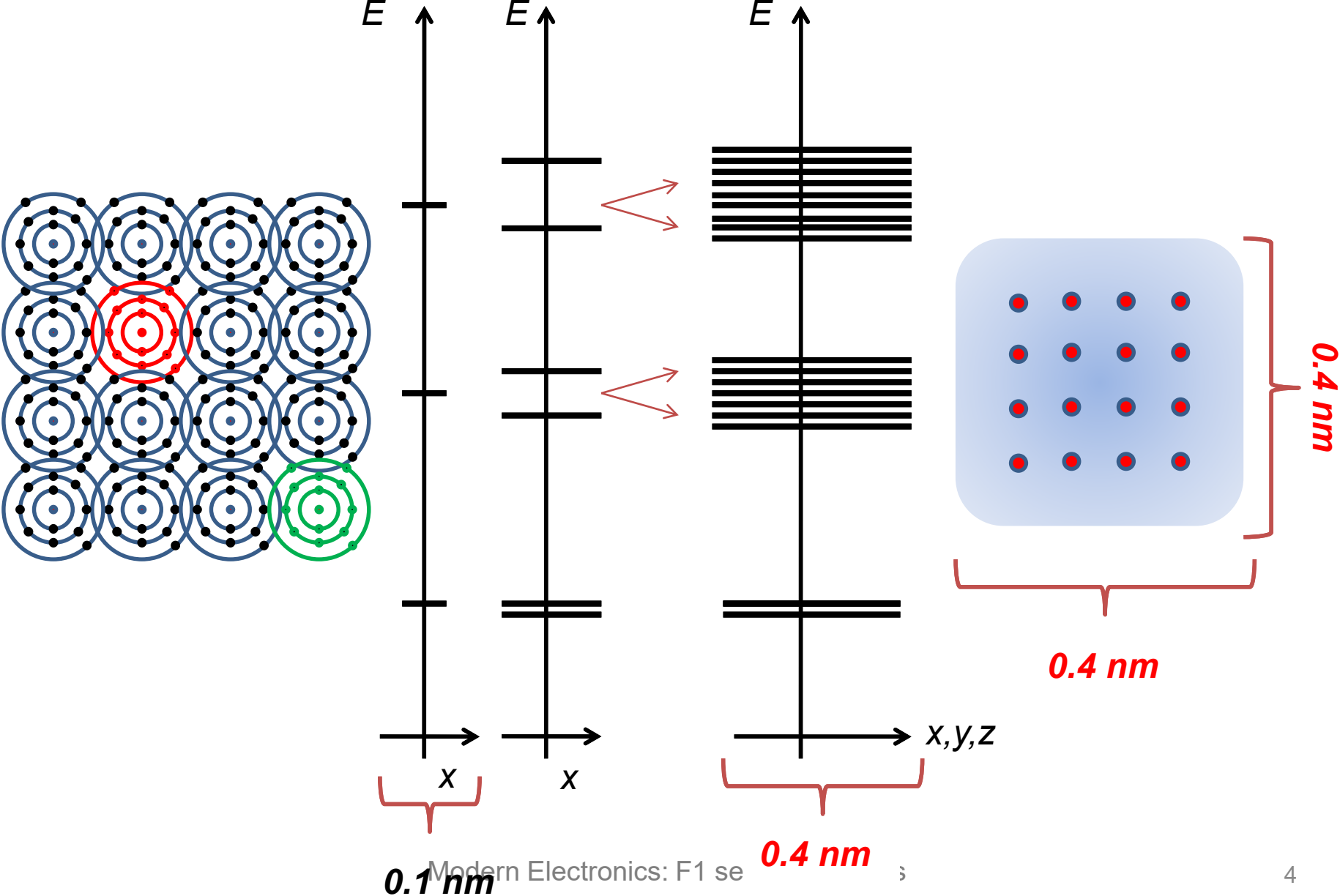


0.1 nm

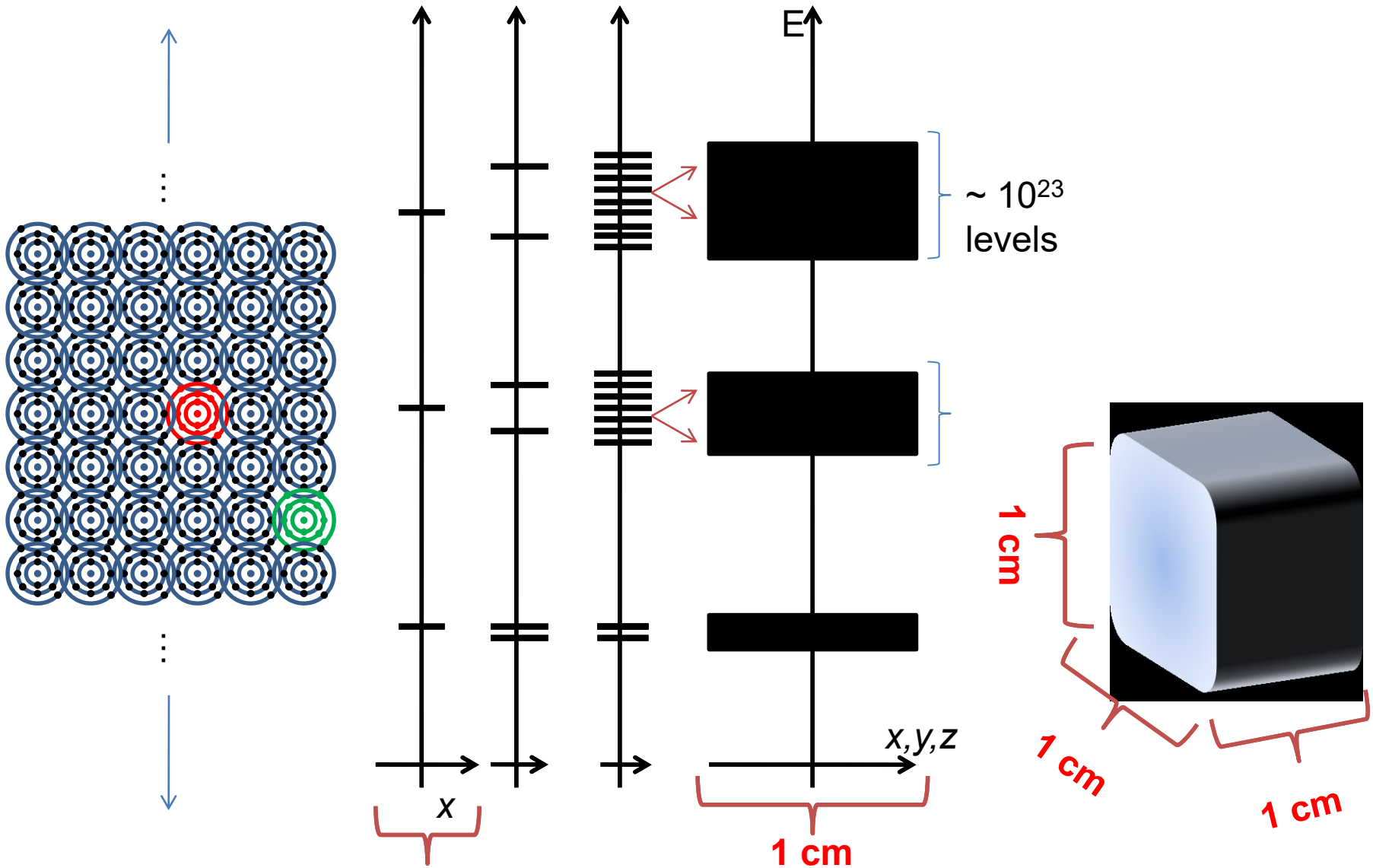
2-atomic molecule – Pauli principle



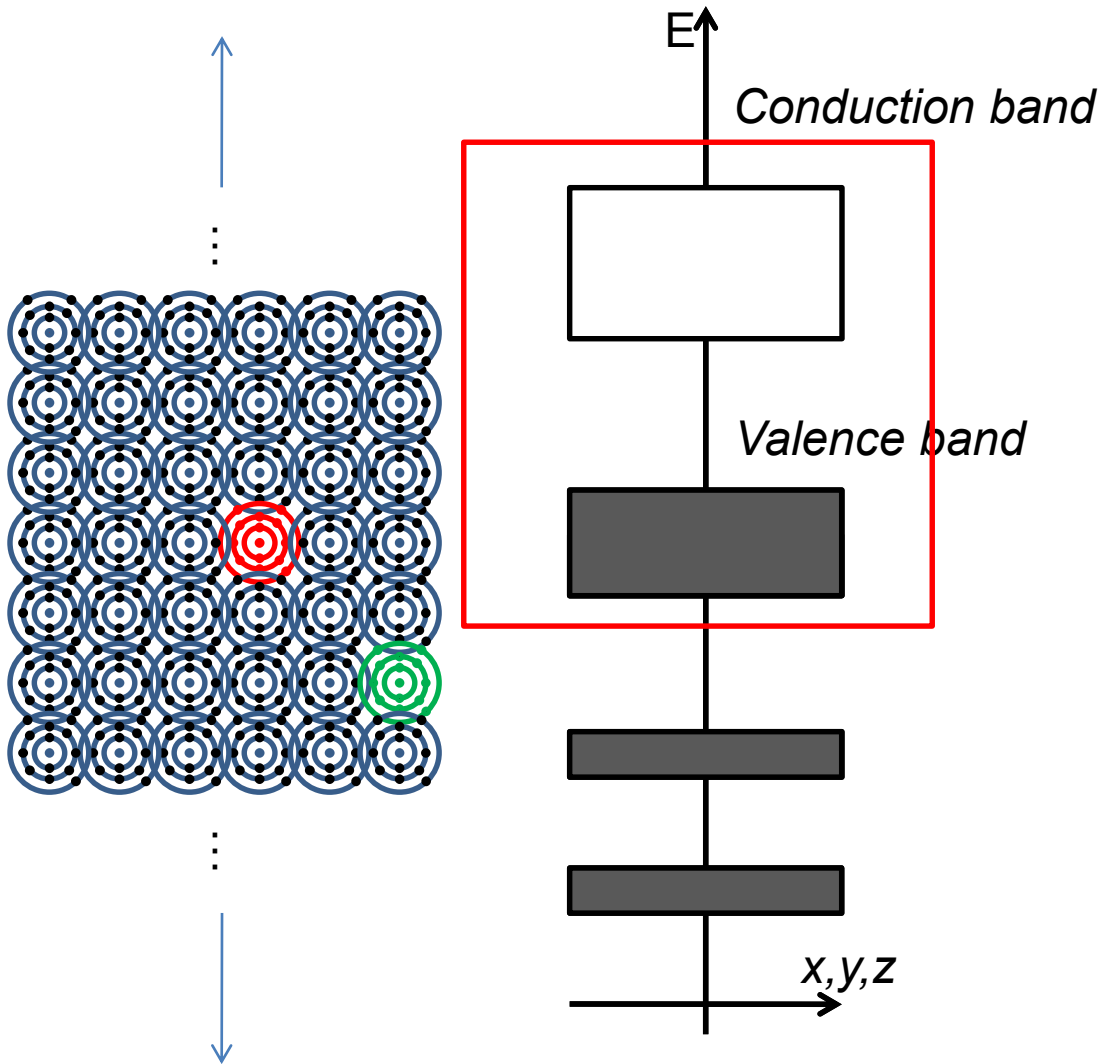
16-atomic molecule



10^{23} -atomic molecule – energy bands



Valence and conduction bands



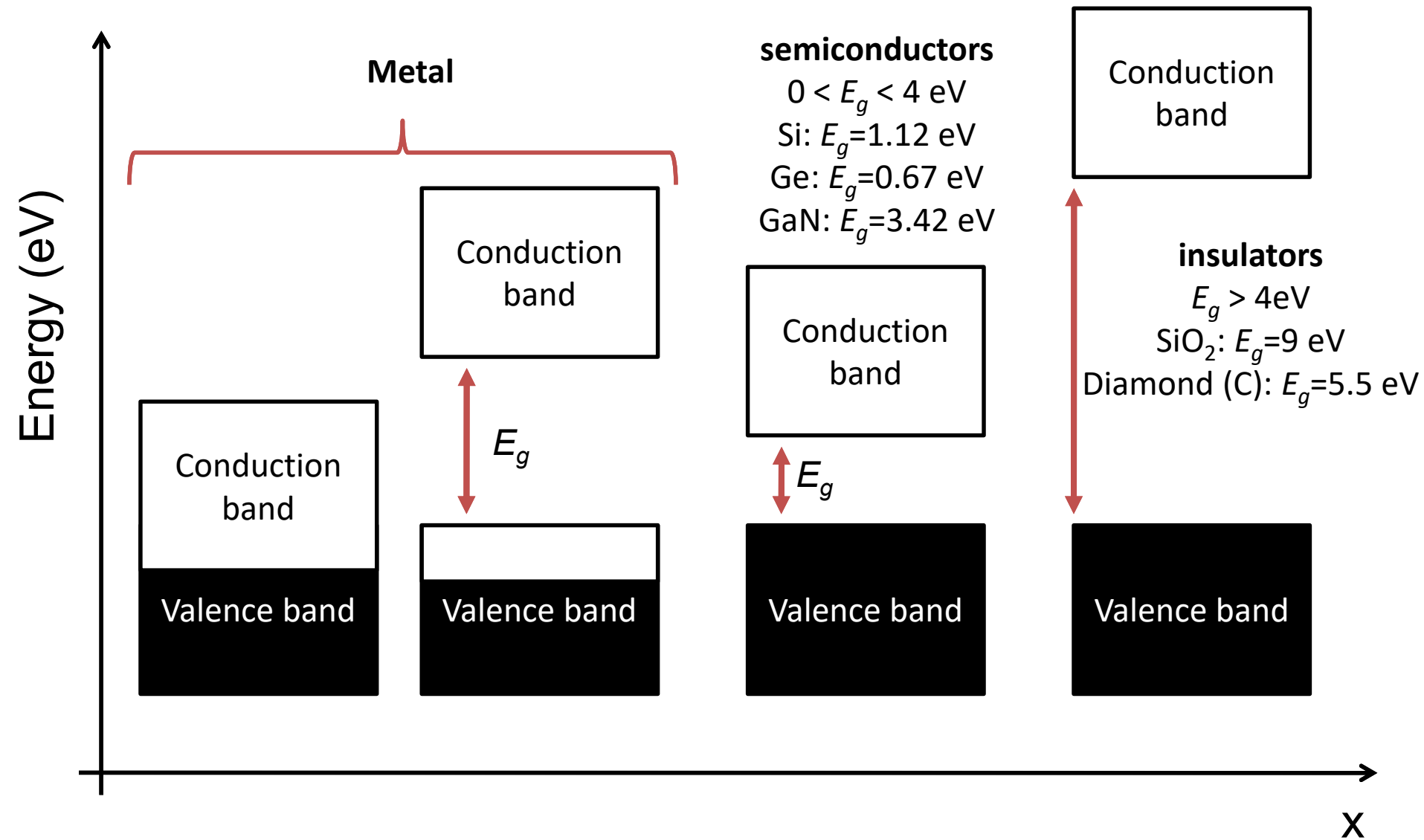
Valence Band: The highest band that has electrons

Conduction Band: The next band with higher energy

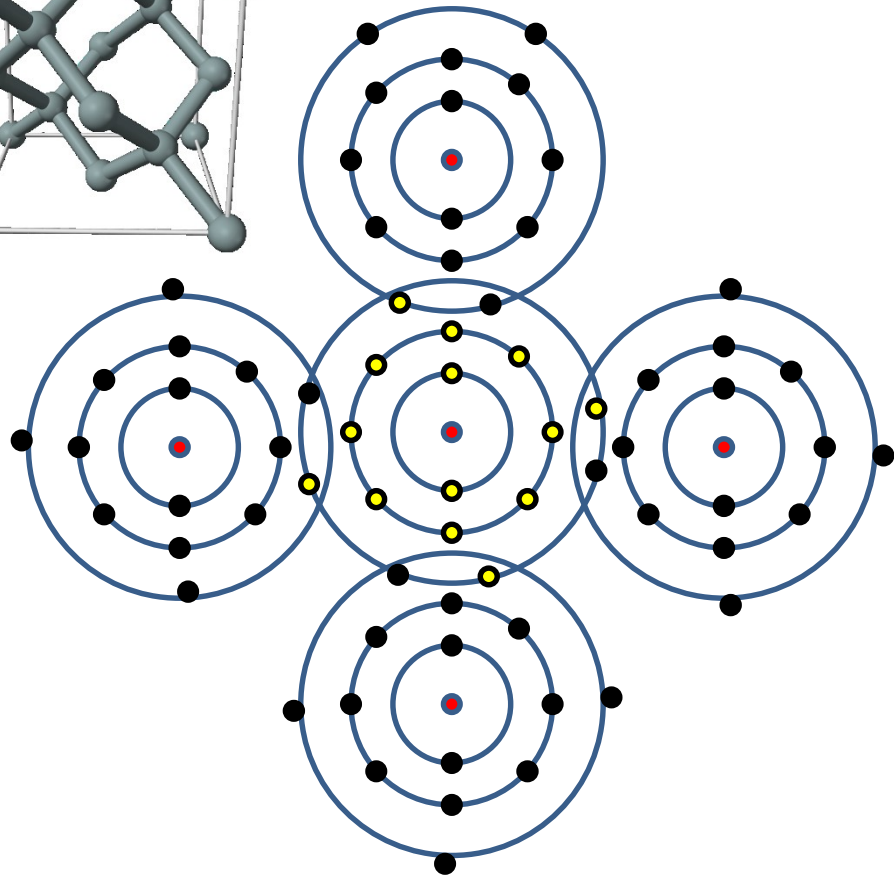
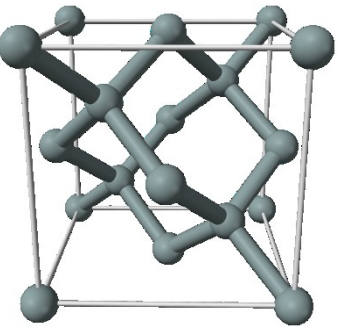
Metal: The valence band is partially filled with electrons

Semiconductor / Insulator: The valence band is filled

metals – semiconductors - insulators



What materials are semiconductors?



Two atom basis (4 neighbours)

4 own valence electrons

total 8 shared electrons in valence shell -> filled!

$$4 + 1 \times 4 = 8$$

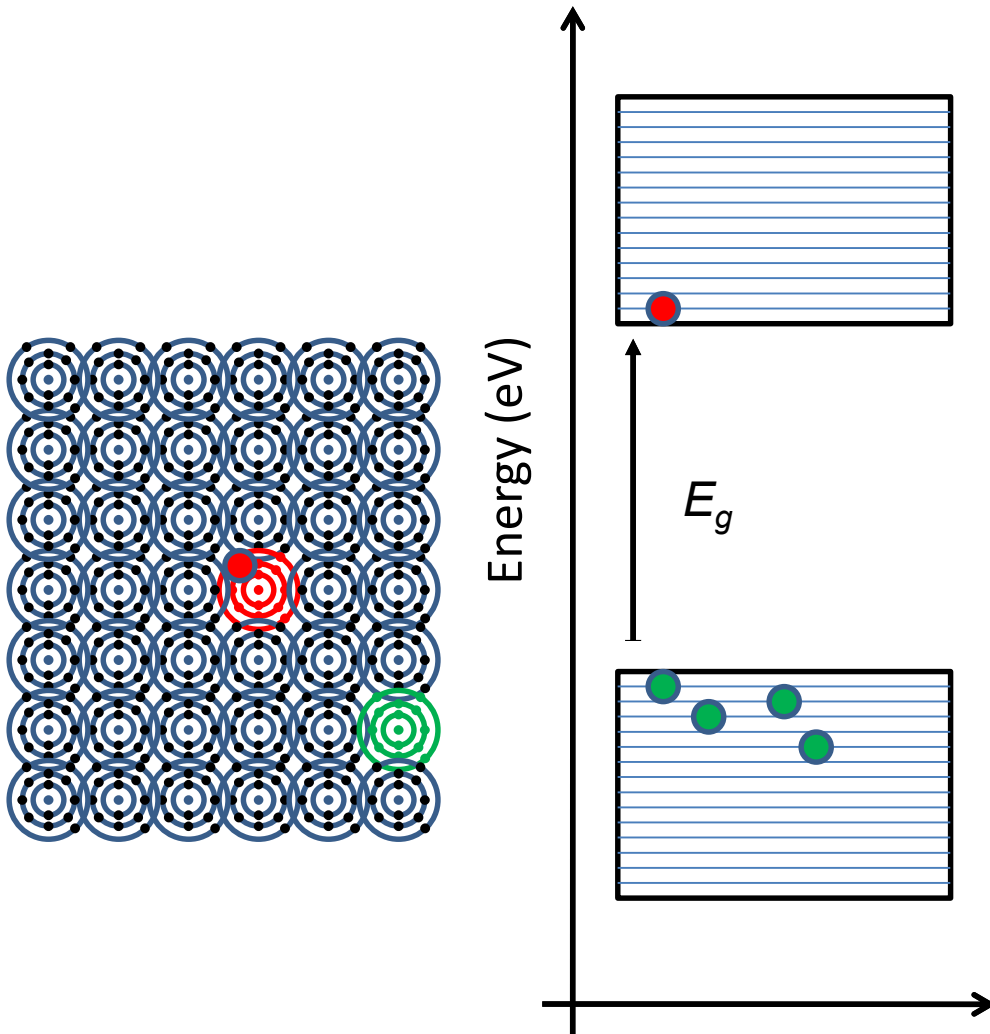
$$3 + 5 = 8$$

III	IV	V
B	C	N
Al	Si	P
Ga	Ge	As
In	Sn	Sb

1	2		3	4	5	6	7	0									
		H						He									
Li	Be		B	C	N	O	F	Ne									
Na	Mg		Al	Si	P	S	Cl	Ar									
K	Ca	Sc	Ti	V	Cr	Mn	Fe	Co	Ni	Cu	Zn	Ga	Ge	As	Se	Br	Kr
Rb	Sr	Y	Zr	Nb	Mo	Tc	Ru	Rh	Pd	Ag	Cd	In	Sn	Sb	Te	I	Xe
Cs	Ba	La	Hf	Ta	W	Re	Os	Ir	Pt	Au	Hg	Tl	Pb	Bi	Po	At	Rn
Fr	Ra	Ac	Rf	Db	Sg	Bh	Hs	Mt	Ds	Rg							

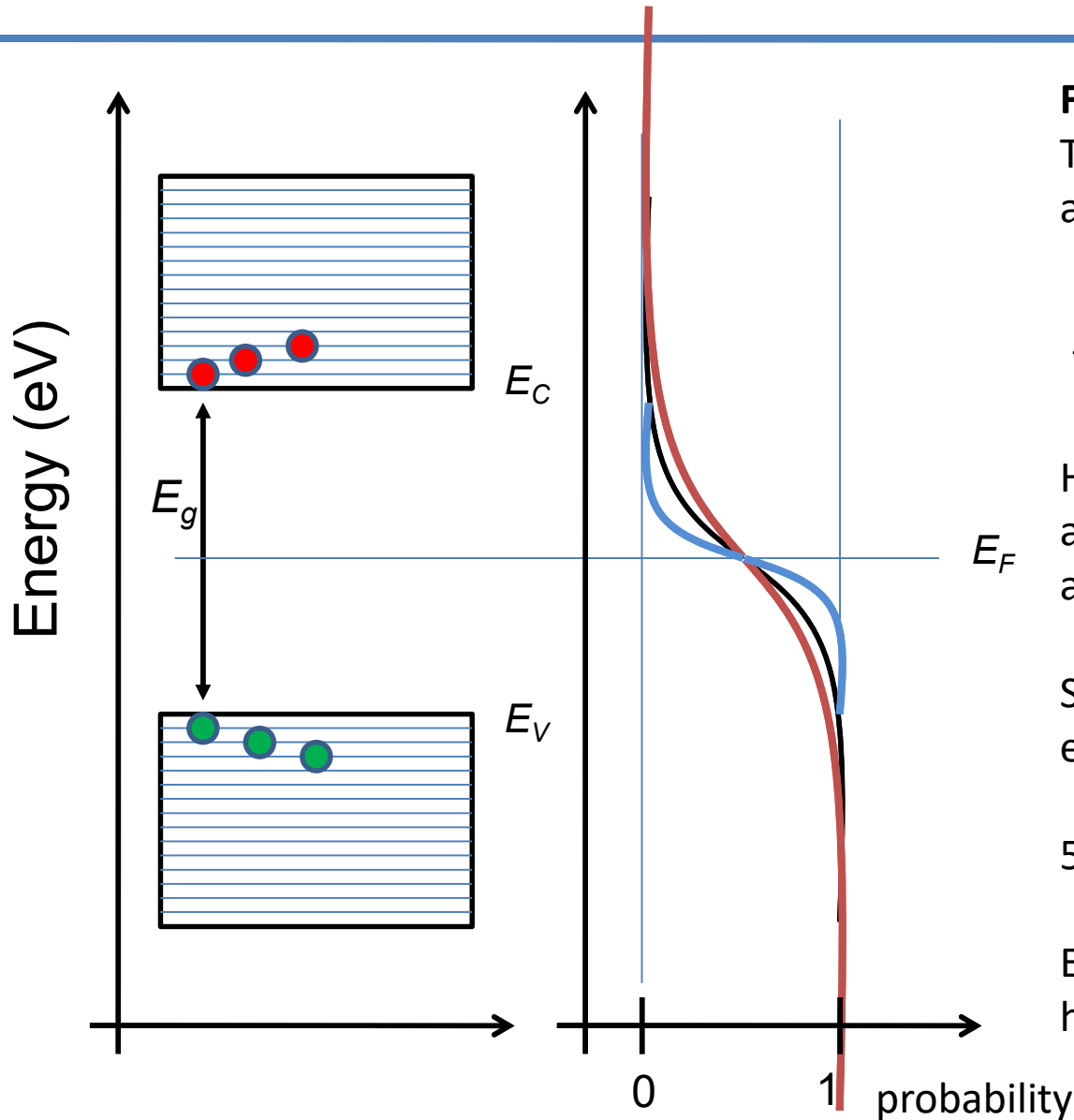
	C	GaP	Si	Ge	InAs	Sn
E_g	5.5 eV	2.24 eV	1.12 eV	0.67 eV	0.34 eV	0
Type	insulator	Semi	cond	uc	tors	metal

Thermal excitation



- Each electrons gets (average) kinetic energy $E_{kin} = 3/2 \cdot kT$
- An electron can be excited to the conduction band
- Higher T or smaller E_g -> more electrons
- electron density in conduction band = n (cm^{-3})
- electron density in valence band = $10^{24} - n$ (cm^{-3})
- p (cm^{-3}): hole density in valence band
- $n=p$ without doping

Thermal excitation – Fermi level



Fermi-Dirac distribution:

The probability of an electron at an energy level E .

$$f(E) = \frac{1}{\exp((E - E_F)/kT) + 1}$$

Higher T – higher probability that a level in the conduction band has an electron.

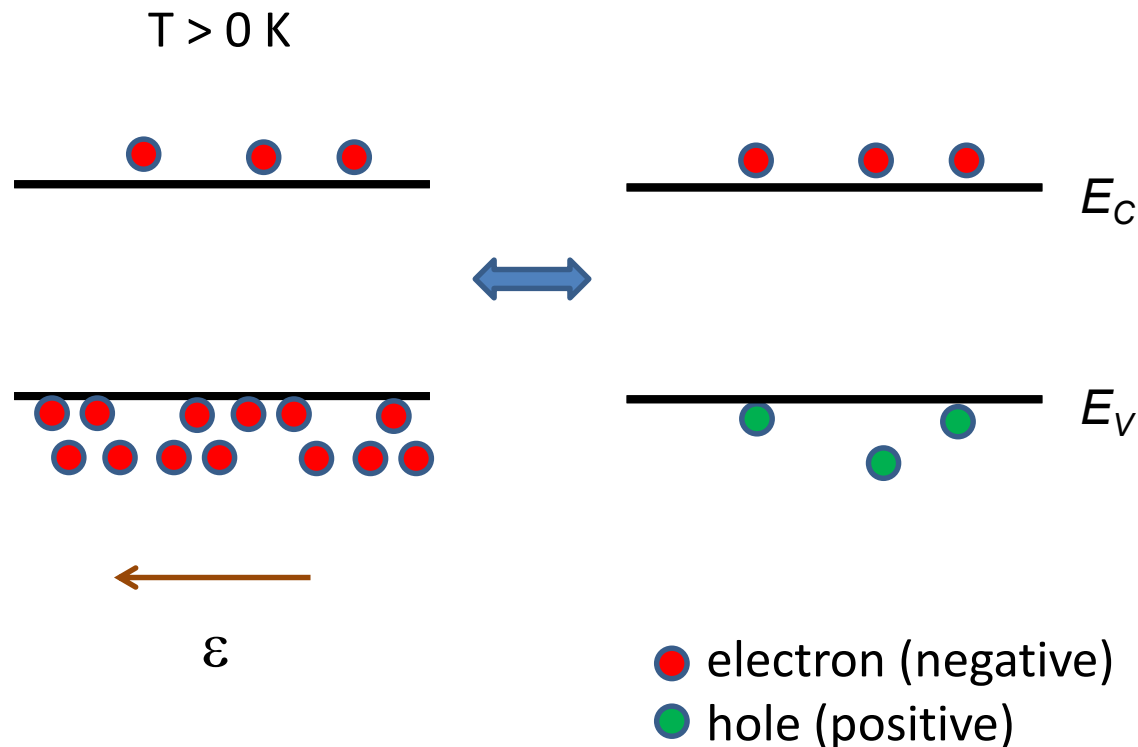
Symmetrical about E_F (Fermi energy).

50% chance to have electron at E_F

Excited electron leave a positive hole in valence band

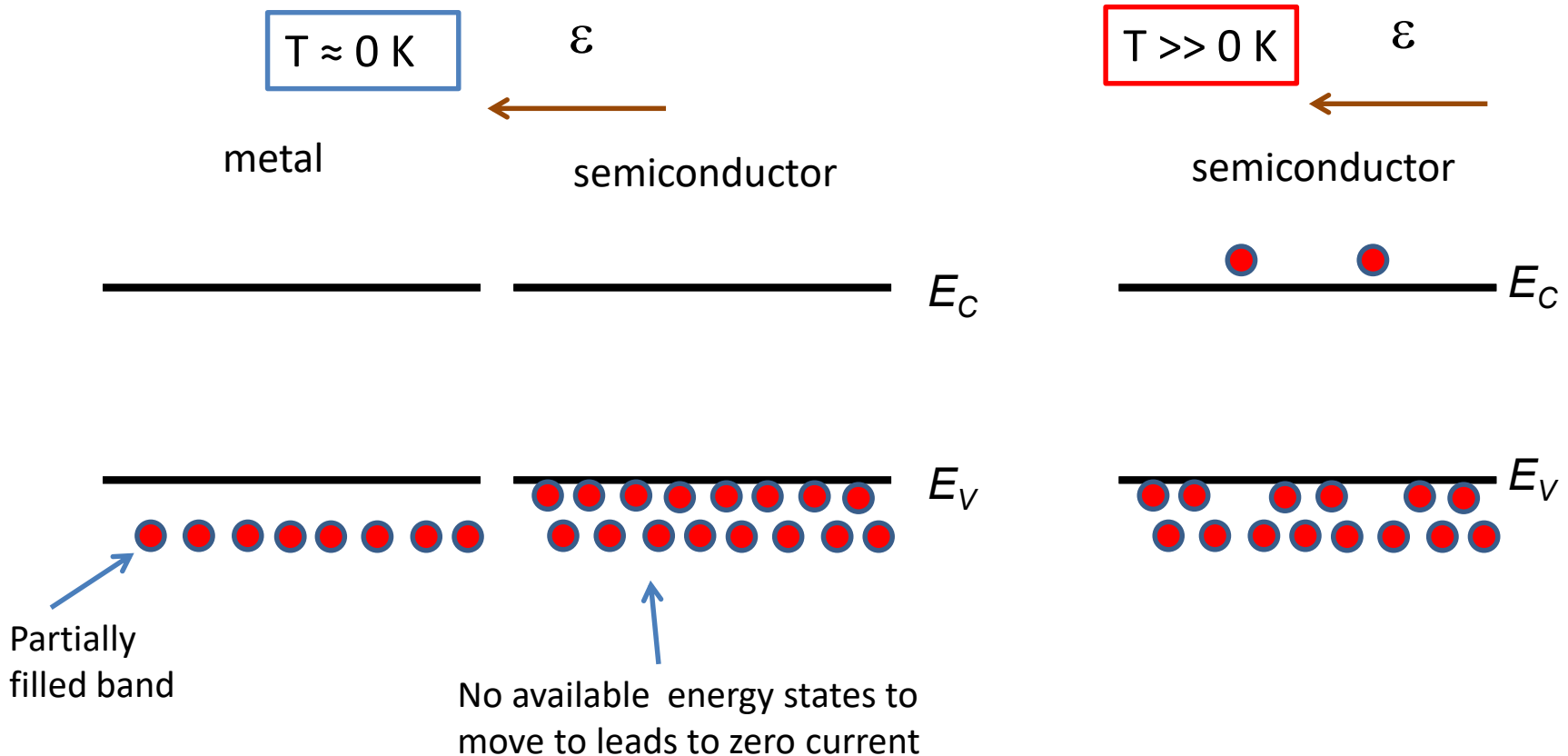
Holes vs electrons

Instead of describing all electrons remaining in valence band, positive holes (missing electrons) are introduced and treated as particles.



Electron transport

- Apply voltage \rightarrow electric field moves charged electrons
- Filled band: $\frac{1}{2}$ of electrons move in one direction, $\frac{1}{2}$ of electrons in the other.
- Need to change velocity of some electrons to get current but all states are filled i.e. need electrons in conduction band.



Carrier concentration

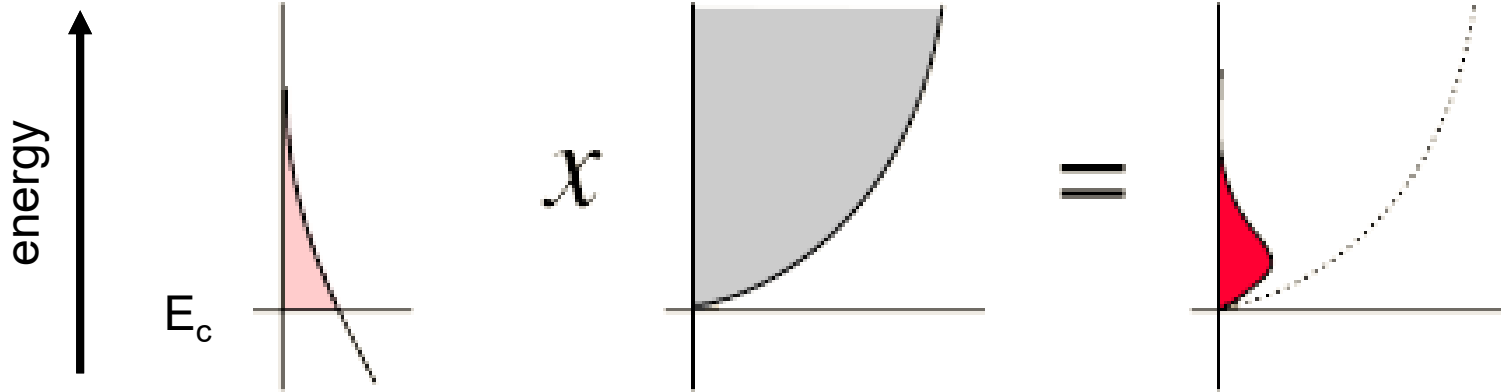
probability of occupying a state

x

number of available states

=

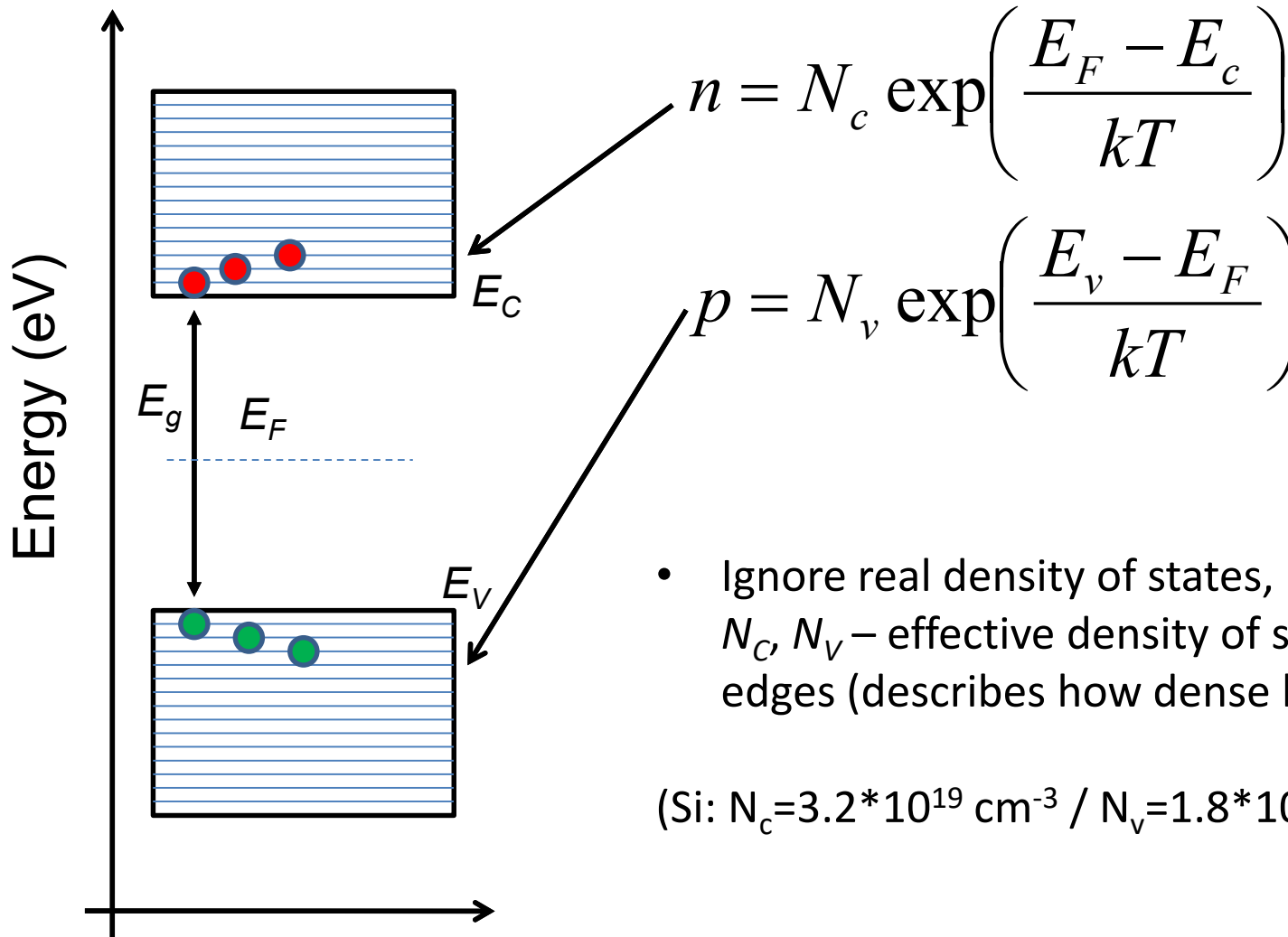
population of conduction band



Fermi-Dirac distribution x density of states = carrier concentration

$$\int_{E_c}^{\infty} dE (D(E) f(E_f, E)) = n$$

Carrier concentration - simplified



- Ignore real density of states, introduce N_c, N_v – effective density of states at band edges (describes how dense levels are)

(Si: $N_c=3.2 \cdot 10^{19} \text{ cm}^{-3}$ / $N_v=1.8 \cdot 10^{19} \text{ cm}^{-3}$)

Intrinsic carrier concentration

Each electron excited from the valence band to the conduction band become a free carrier available for conduction

Intrinsic semiconductor:

- $n=p=n_i$ (intrinsic carrier concentration)
- E_F is in the middle of the band gap

$$n_i = \sqrt{n \cdot p} = \sqrt{N_c N_v} \exp\left(\frac{-E_g}{2kT}\right)$$

T=300K

Si

$E_g=1.11\text{eV}$

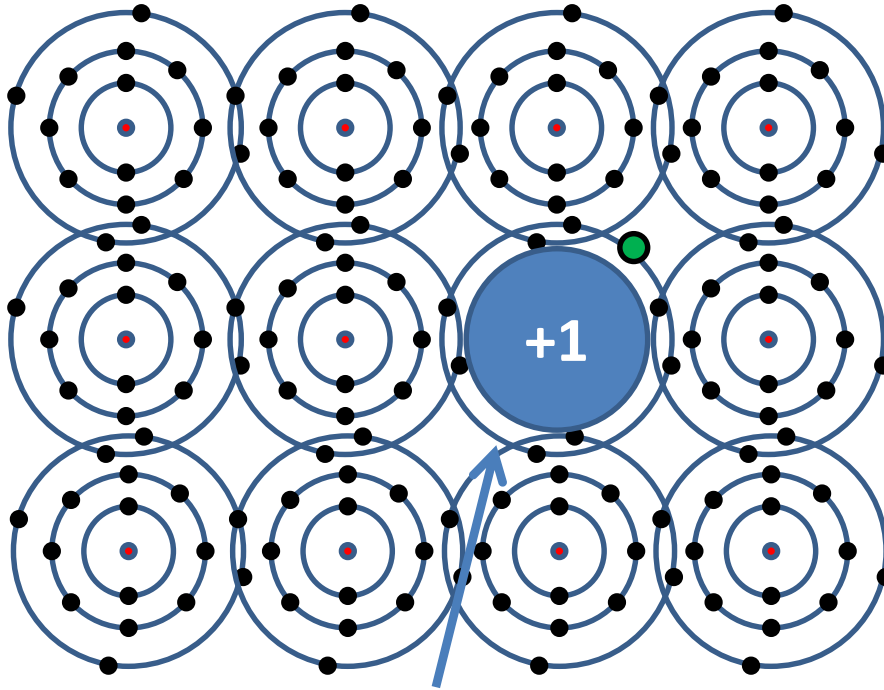
$n_i=1 \times 10^{10} \text{ cm}^{-3}$

Ge

$E_g=0.67 \text{ eV}$

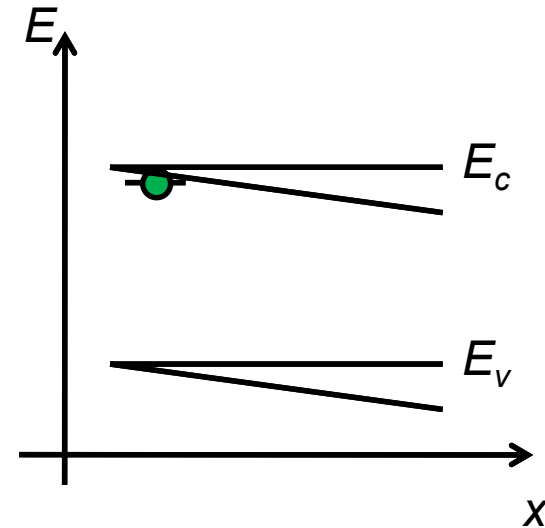
$n_i= 2 \times 10^{13} \text{ cm}^{-3}$

Doping with donor atoms: n-type



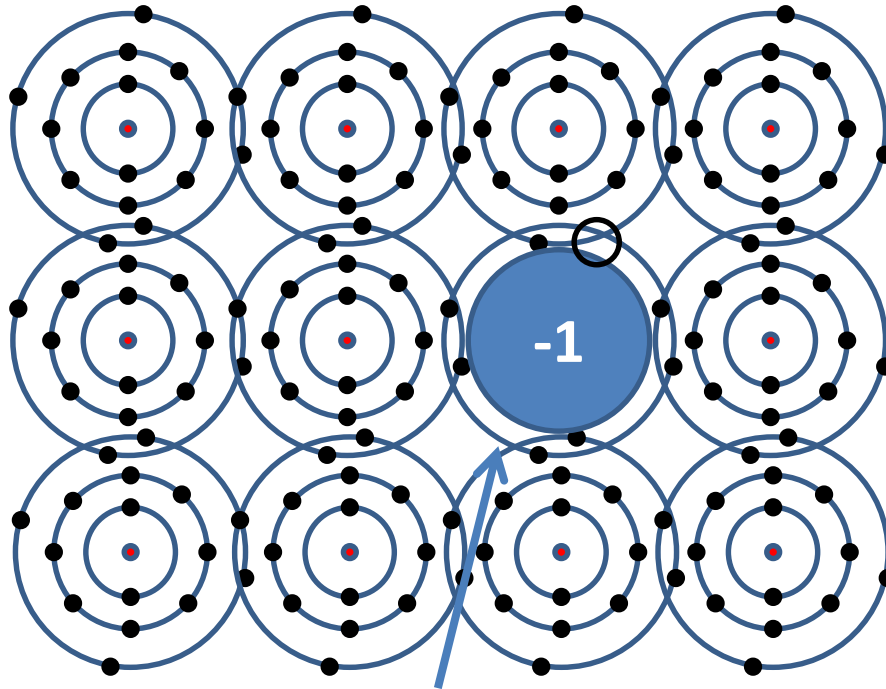
P – atom
5 valence electrons

Donates electron to the conduction band (mobile)
Ionized atom – positive (immobile)

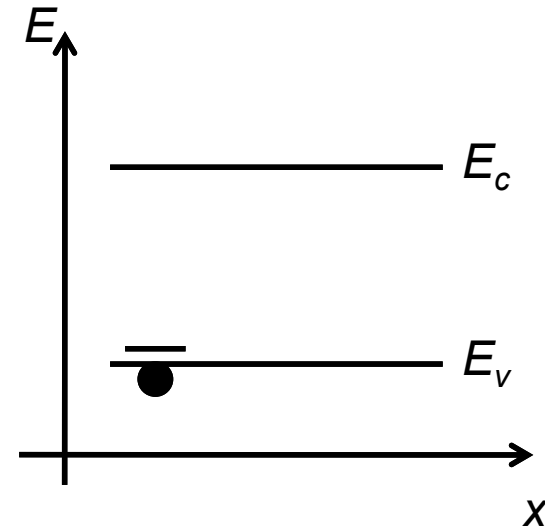


III	IV	V
B	C	N
Al	Si	P
Ga	Ge	As
In	Sn	Sb

Doping with acceptor atoms: p-type



Al – atom
3 valence electrons



Captures electron -> extra hole to the valence band (mobile)
Ionized atom – negative (immobile)

III	IV	V
B	C	N
Al	Si	P
Ga	Ge	As
In	Sn	Sb

Doping – extrinsic semiconductor

$$\left. \begin{aligned} n &= N_c \exp\left(\frac{E_F - E_c}{kT}\right) \\ p &= N_v \exp\left(\frac{E_v - E_F}{kT}\right) \end{aligned} \right\} \text{Mass action law}$$
$$np = N_c N_v \exp\left(\frac{-E_g}{kT}\right) = n_i^2$$

↓

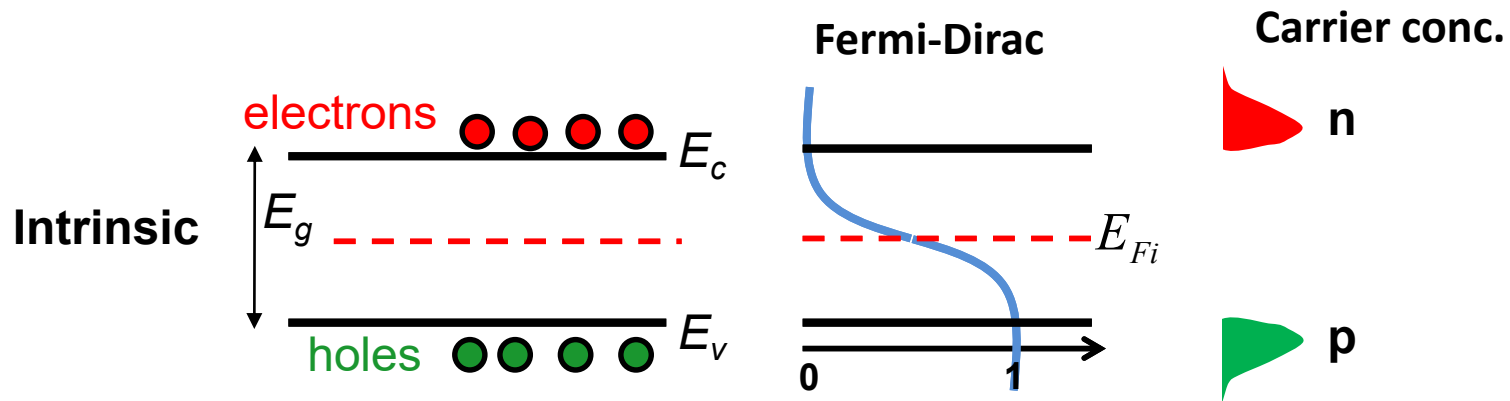
$$\boxed{n \cdot p = n_i^2}$$

Independent of doping

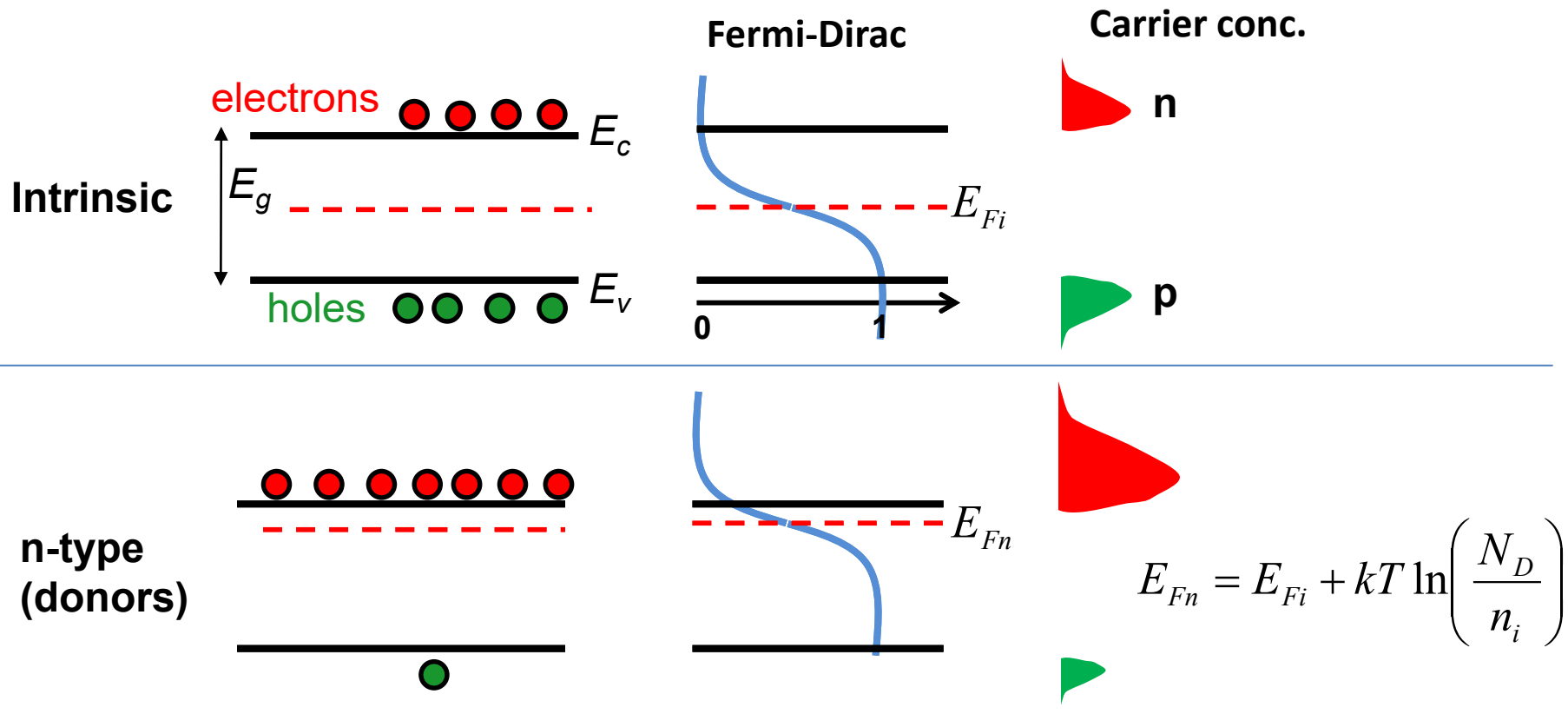
- N_D : donor atom density (cm^{-3}) / N_A : acceptor atom density (cm^{-3})
- For $N_D \gg n_i$ ($N_A=0$) the doping dominates majority carrier concentration

$$\boxed{n=N_D \text{ and } p=n_i^2/N_D}$$

doping – carrier density

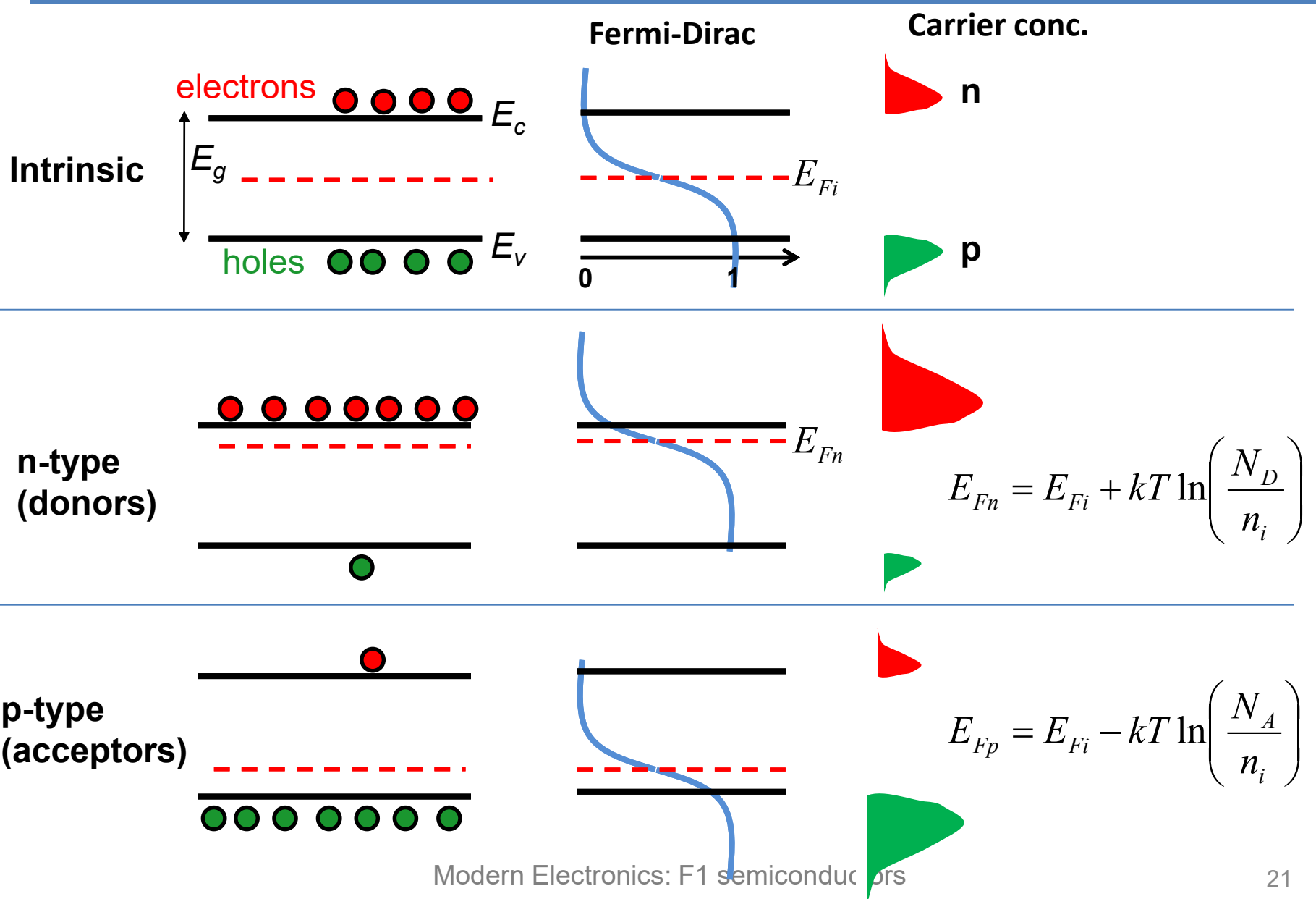


doping – carrier density



$$E_{Fn} = E_{Fi} + kT \ln\left(\frac{N_D}{n_i}\right)$$

doping – carrier density



Transport - drift

$$J_p = q p \overbrace{\mu_p}^{v_d} \varepsilon$$

$$J_n = q n \mu_n \varepsilon$$

$$J = J_n + J_p$$

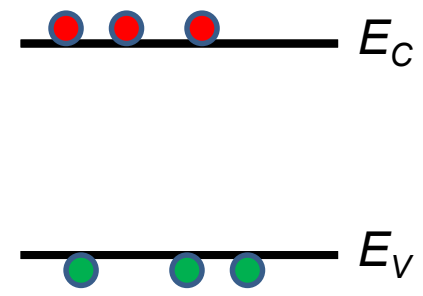
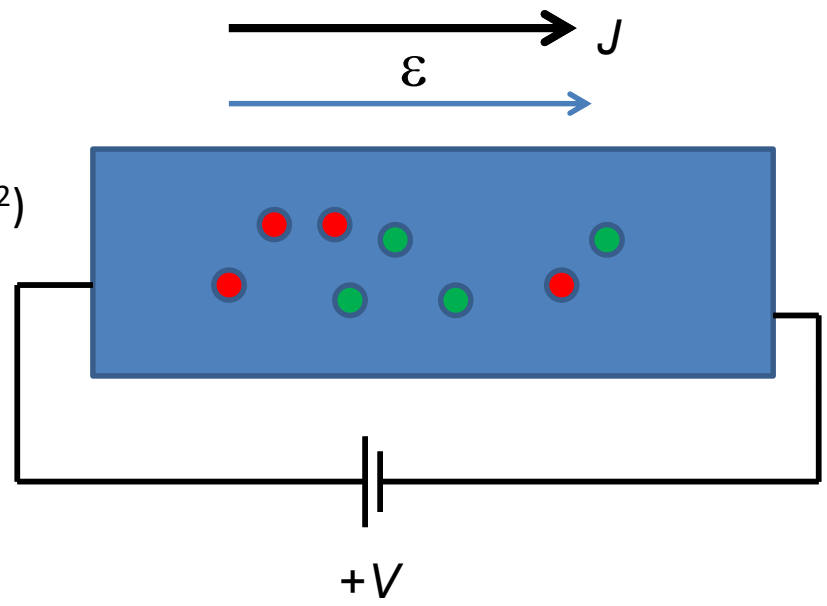
Hole current density (A/cm²)

Electron current density (A/cm²)

$$\sigma = q(\mu_n n + \mu_p p)$$

$$\rho = \frac{1}{q(\mu_n n + \mu_p p)}$$

μ_n / μ_p – electron / hole mobility (cm²/Vs)
 n / p – electron / hole concentration (cm⁻³)
 $\sigma = 1/\rho$ = conductivity (S/m)
 ρ = resistivity (Ω m)

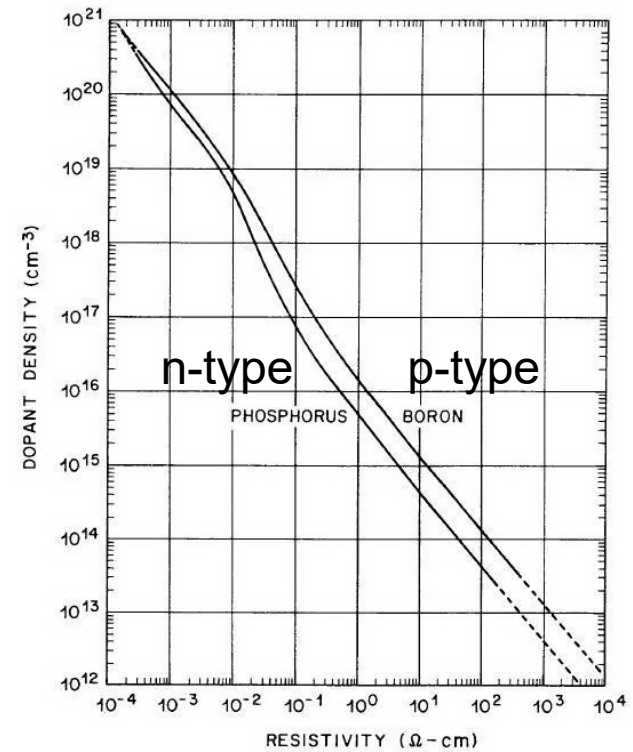
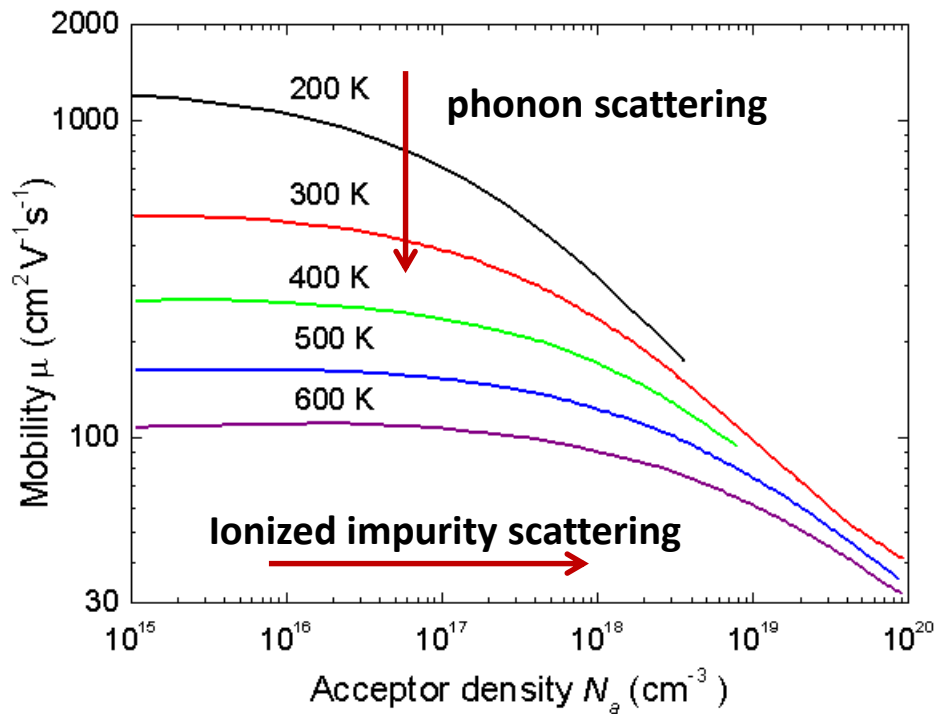


Transport – effect of doping

$$J_n = qn v_d = qn \mu_n \mathcal{E}$$

n : controlled by doping

μ_n : determined by intrinsic semiconductor properties + scattering



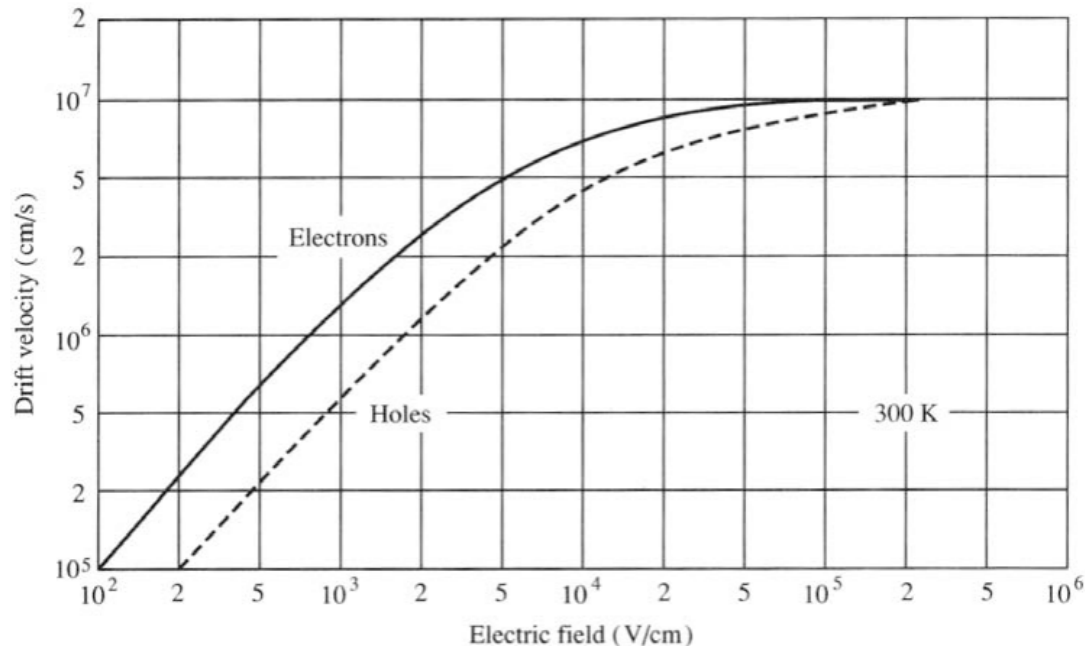
Conversion between resistivity and dopant density in silicon.

Velocity saturation

- At high electric fields ($\epsilon_c \approx 1.5 \times 10^6$ V/m) electrons can emit optical phonons (lattice vibrations) -> velocity saturates

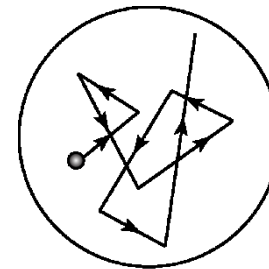
$$J = qn v_d = qn \mu_n(\epsilon) \epsilon$$

$$v_d = \frac{\mu_n \epsilon}{1 + \epsilon / \epsilon_c} \begin{cases} \epsilon \ll \epsilon_c \rightarrow v_d \approx \mu_n \epsilon \\ \epsilon \gg \epsilon_c \rightarrow v_d \approx \mu_n \epsilon_c = v_{sat} \end{cases}$$

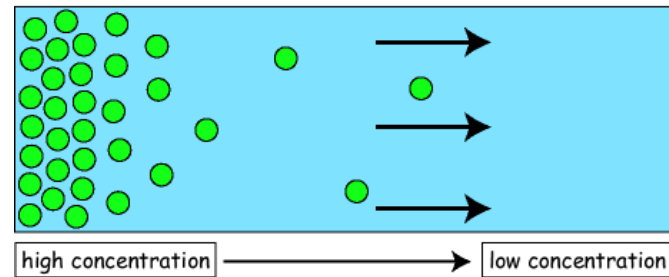


Transport - diffusion

- Random thermal motion gives movement of particles from high to low concentration
- No external forces
- No particle interaction
- Rate depends on concentration gradient

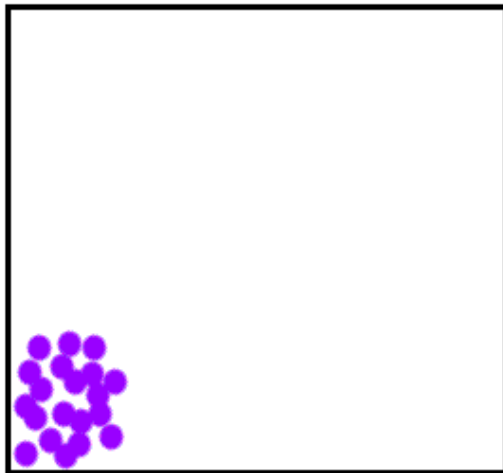


Brownian Movement



high concentration

low concentration

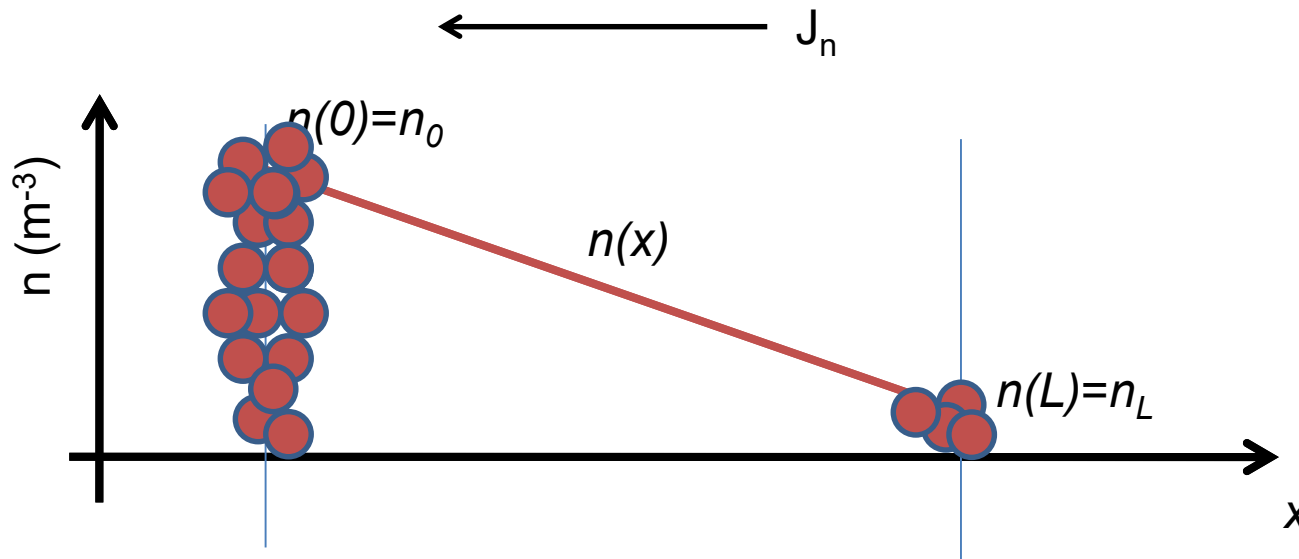


Transport - diffusion

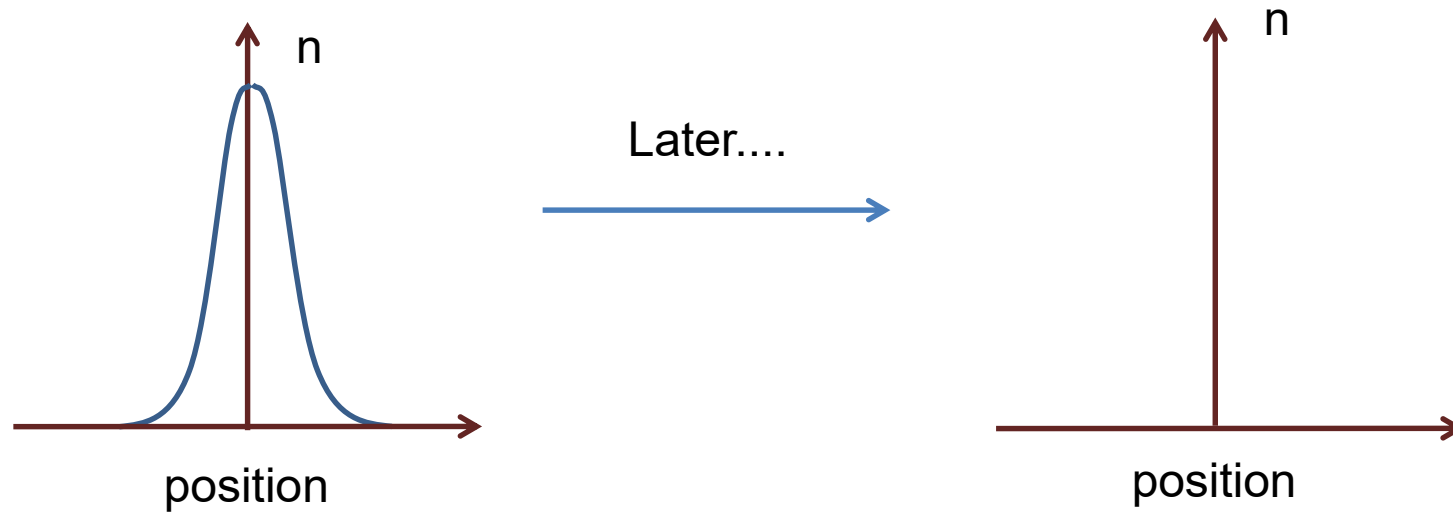
Diffusion current given by gradient of electron (or hole) concentration

$$J_n = qD_n \frac{dn(x)}{dx} = q \left(\frac{kT}{q} \mu_n \right) \frac{dn(x)}{dx} = qV_T \mu_n \frac{dn(x)}{dx}$$

No addition/removal of carriers between $0 < x < L$ -> constant current -> linear concentration decrease



2 min exercise – drift/diffusion



Sketch carrier distribution later with

1. No electric field
2. E-field in pos. direction (->)

Summary

- Discrete atomic energy levels become bands when atoms are joined in a crystal.
- Semiconductors = filled valence band, no electrons in conduction band (at T=0).
Band gap with no allowed states.
- Carrier concentration (n) = Fermi-dirac distribution * density of states
- Doping:
 - Donors (group V): adds mobile negative electrons and positive static ions.
Moves Fermi level towards conduction band.
 - Acceptors (group III): adds mobile positive holes and negative static ions.
Moves Fermi level towards valence band.
- Carrier transport:
 - Drift: electric field moves charged particles. Depends on field strength.
 - Diffusion: random motion moves particles from high to low concentration.
Depends on concentration gradient.

$$n = N_c \exp\left(\frac{E_F - E_c}{kT}\right)$$

$$n \cdot p = n_i^2 \quad n=N_D \text{ and } p=n_i^2/N_D \text{ for } N_D \gg n_i$$

$$J_n = J_{n,drift} + J_{n,diff} = qn\mu_n \mathbf{E} + qD_n \frac{dn}{dx}$$

pn- junctions

Charge distribution -> electric field -> potential

Current transport

Breakdown mechanisms

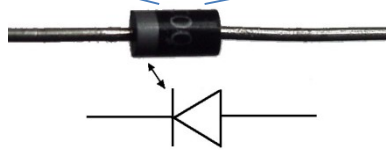
Small-signal model

Depletion / diffusion capacitances

Reading: (Sedra/Smith 7th edition)
1.10-1.12, 3.1 - 3.3

Why pn-junctions?

diode
LED
Solar cell

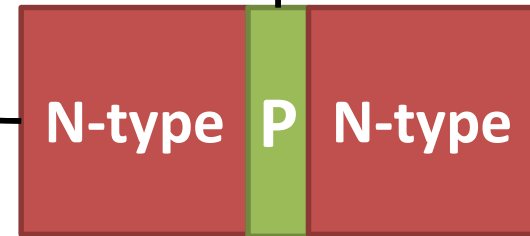


BJT

Base

Emitter

Collector

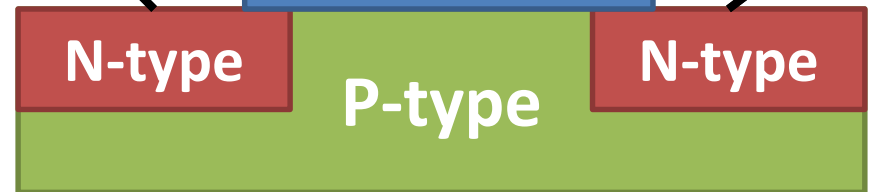


MOSFET

Gate

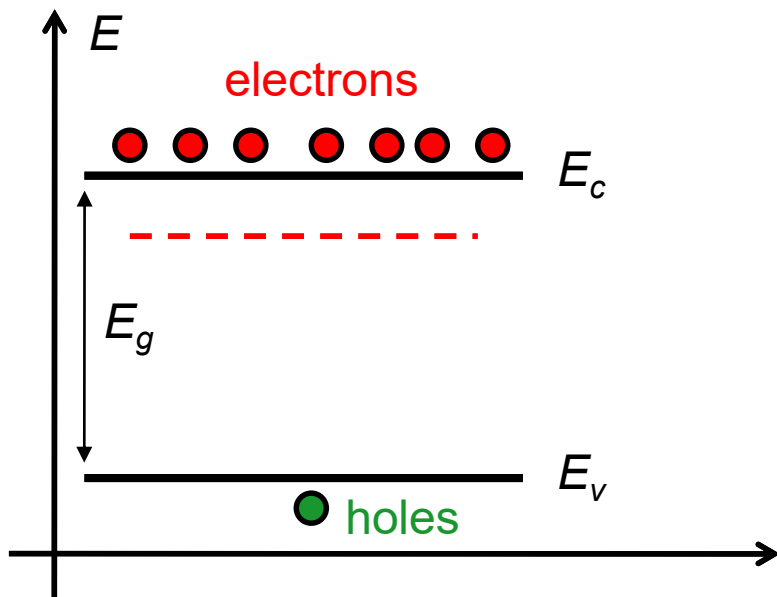
Source

Drain



Substrate

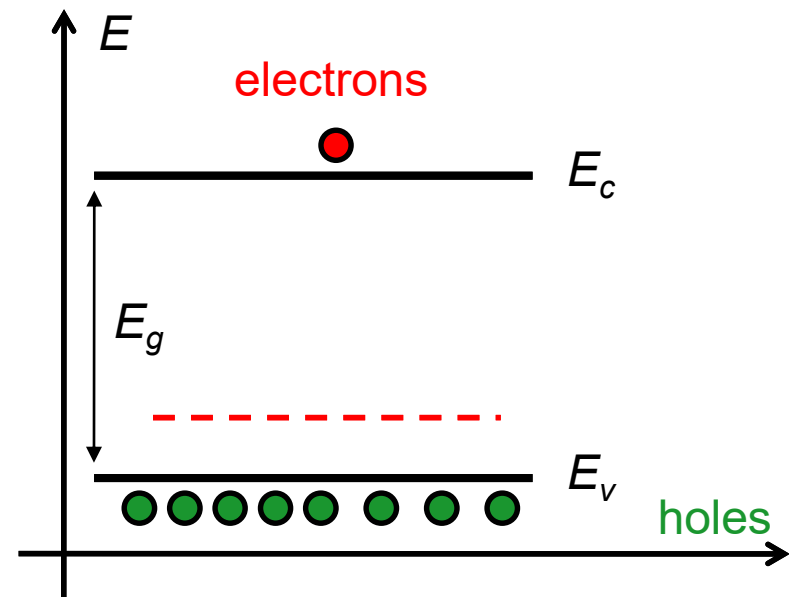
N - type



N_D – donor concentration
 n_{n0} – electron (majority) concentration
 p_{n0} – hole (minority) concentration

Electrons: mobile, negative
Ionized donors: not mobile, positive

P - type



N_A – acceptor concentration
 p_{p0} – hole (majority) concentration
 n_{p0} – electron (minority) concentration

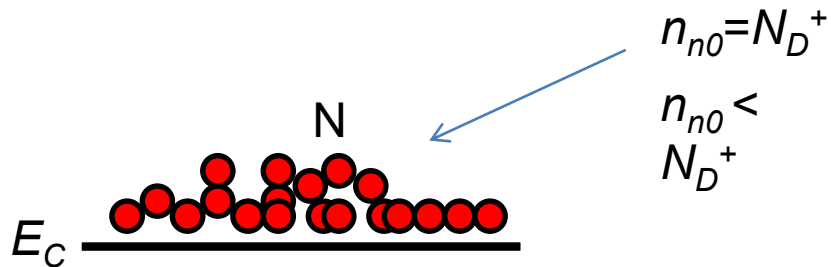
holes: mobile, positive
Ionized acceptors: not mobile, negative

Recombination

$$n_0 \cdot p_0 = n_i^2 \quad \text{In equilibrium}$$

Important for base current in BJTs

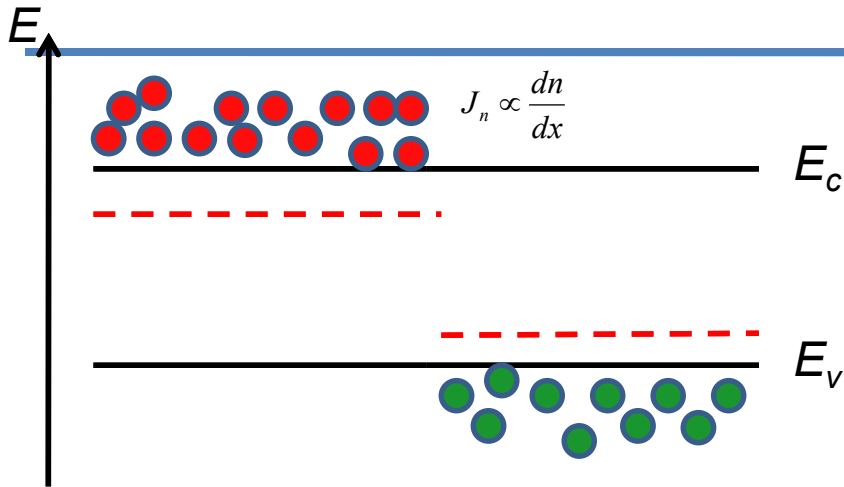
If there is an excess number free carriers $np > n_i^2$ electrons can recombine with holes to reach equilibrium



Three electrons recombine leaving three positive ionized donor atoms

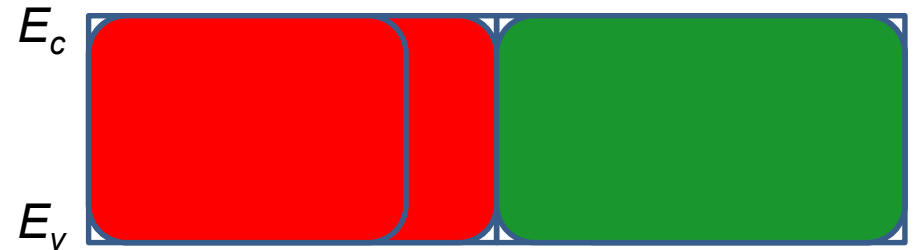
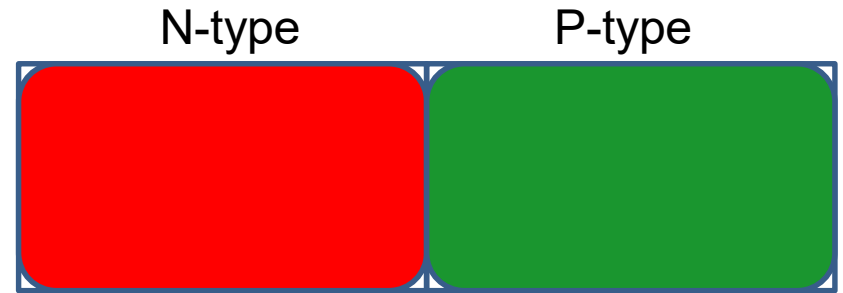


PN-junction – band structure



+ Positive donor
- Negative Acceptor

Free electrons
Free holes



Large conc. difference -> large diffusion current
No ϵ -field – no drift current

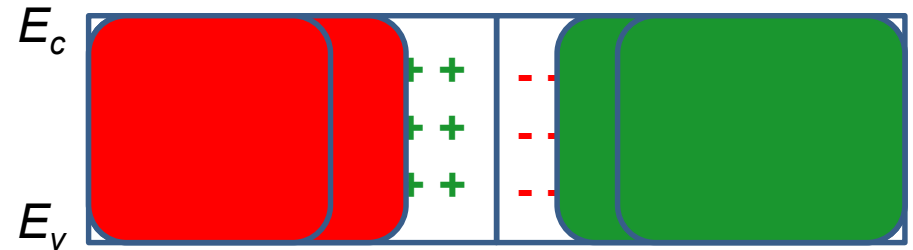
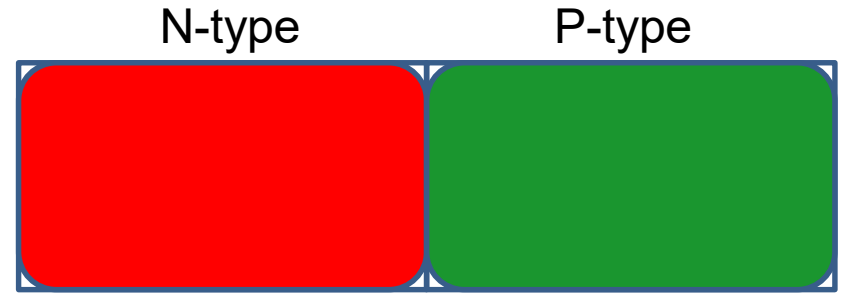
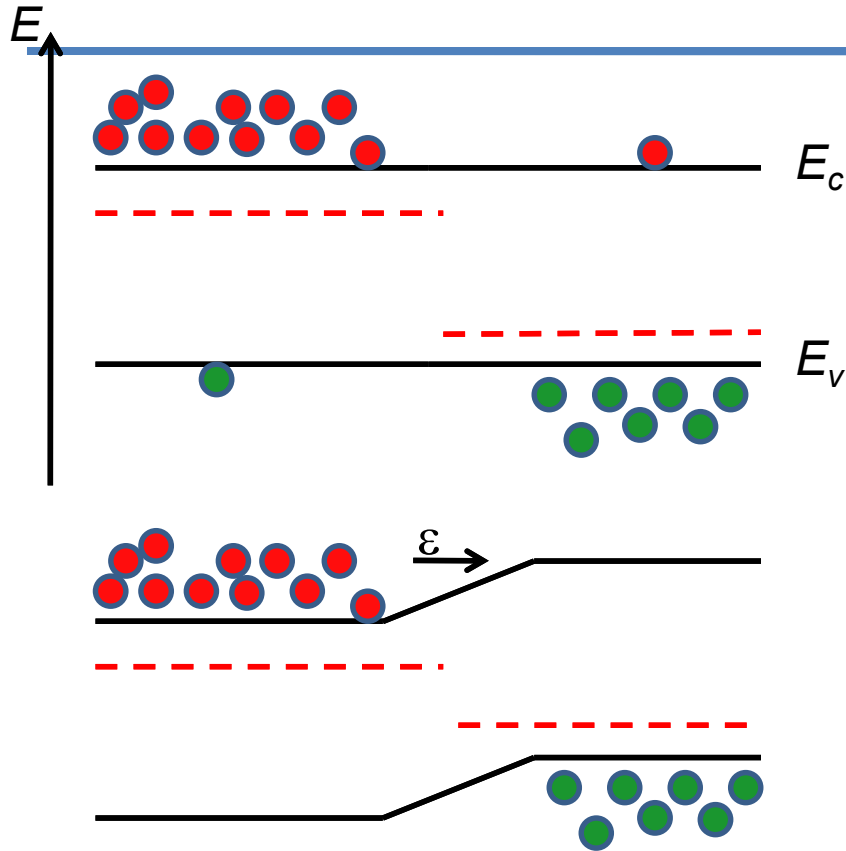
$$I_n = qA\mu_n \left[n \cdot \epsilon + V_T \frac{dn(x)}{dx} \right]$$



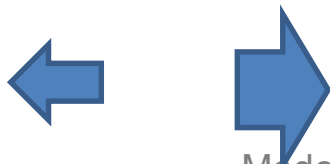
PN-junction – band structure

+ Positive donor
- Negative Acceptor

Free electrons
Free holes



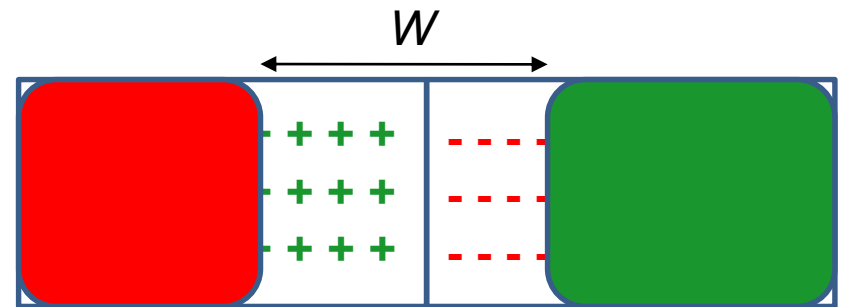
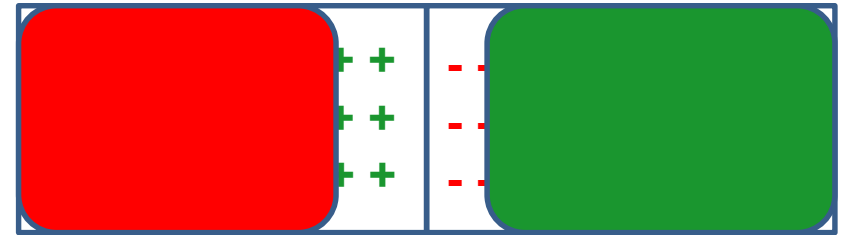
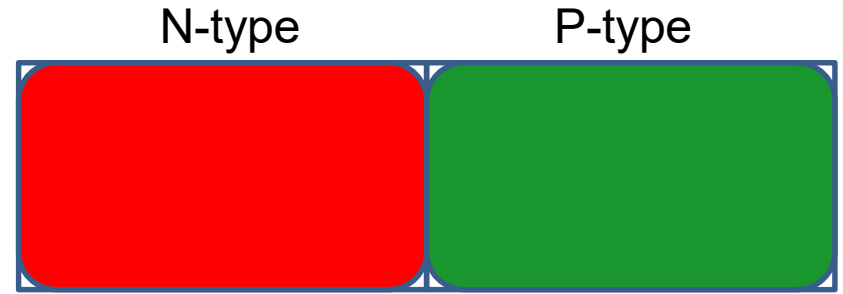
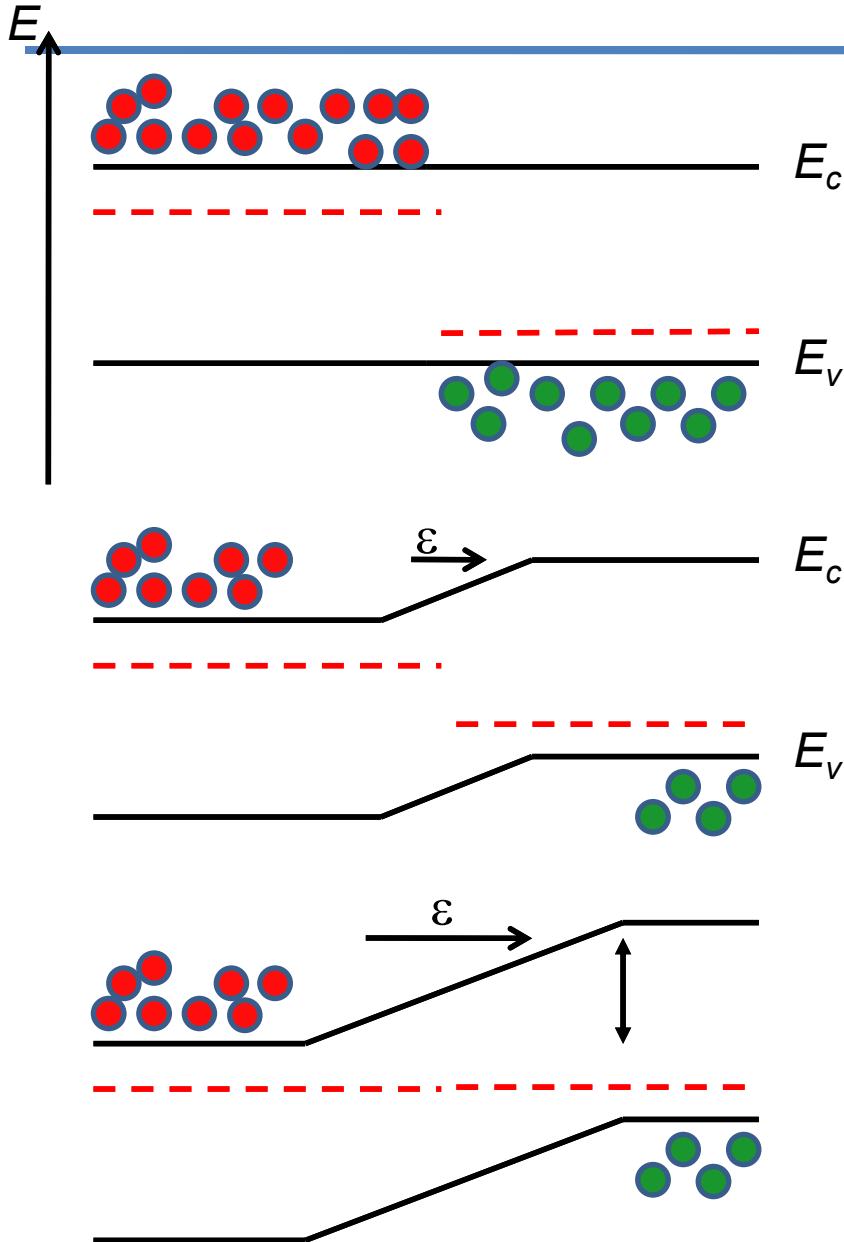
$$I_n = qA\mu_n \left[n \cdot \epsilon + V_T \frac{dn(x)}{dx} \right]$$



PN-junction – band structure

+ Positive donor
- Negative Acceptor

Free electrons
Free holes



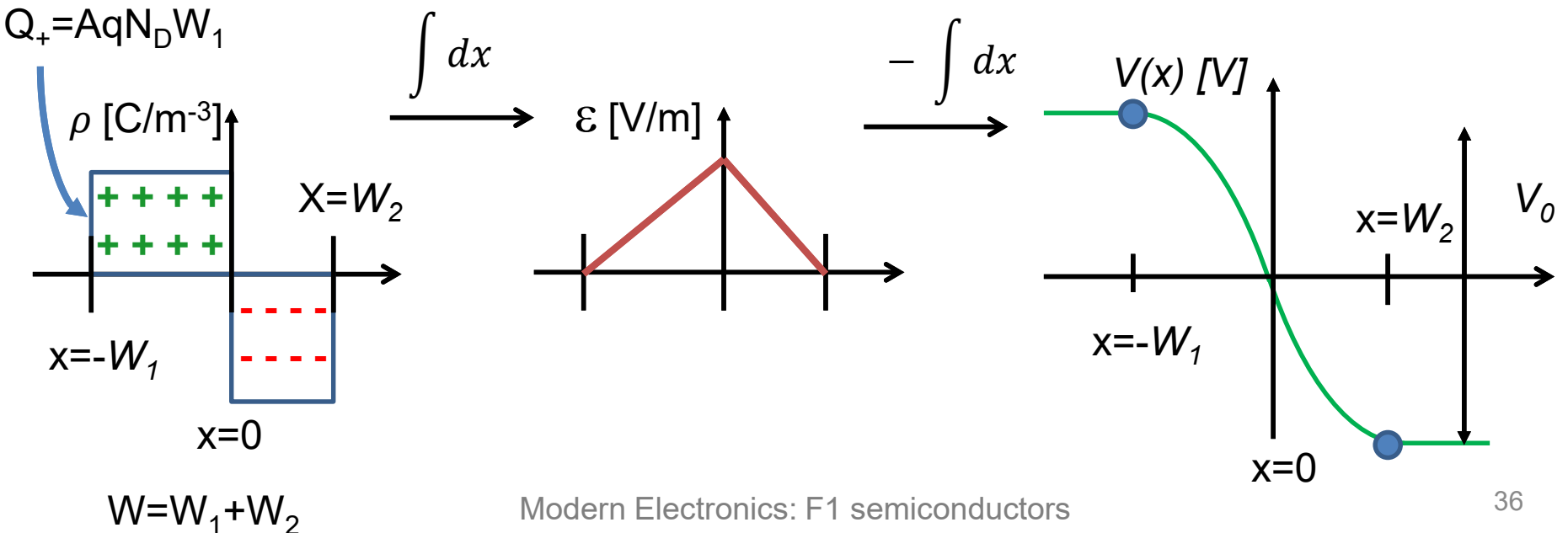
No free carriers in depletion region,
charge neutral outside

charge density -> electric field -> potential

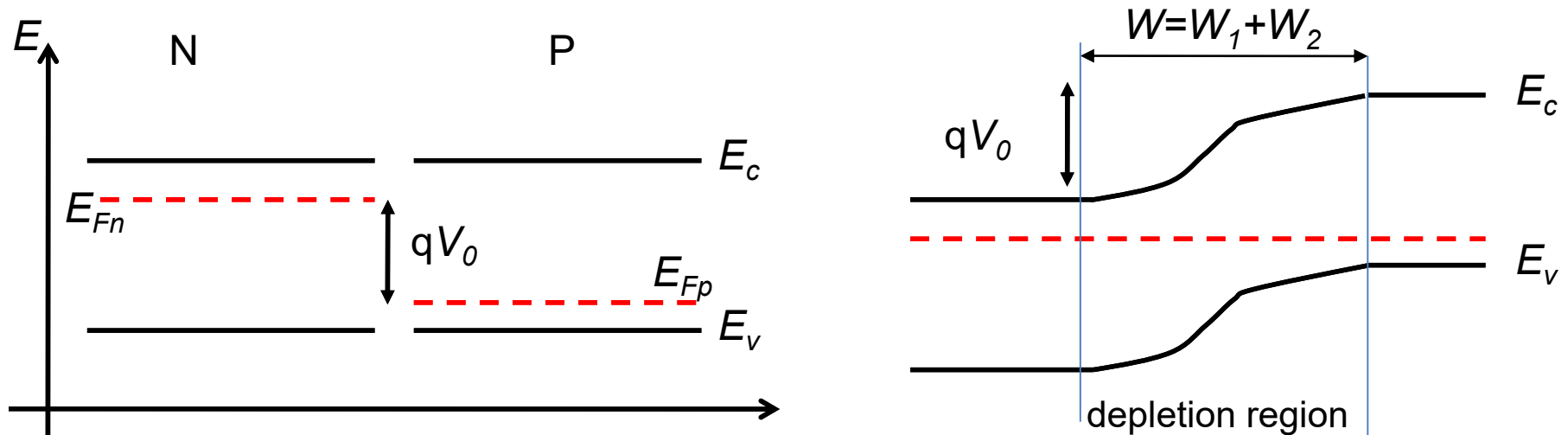
Poisson equation $\frac{\rho(x)}{\epsilon_s} = \frac{d\varepsilon(x)}{dx} = -\frac{d^2V(x)}{dx^2}$

Depletion width $W = \sqrt{\frac{2\epsilon_s}{q} \left(\frac{1}{N_A} + \frac{1}{N_D} \right) V_0}$

- ρ charge density [C/m³]
- ϵ_s permittivity [F/m]
- ε electric field [V/m]
- V potential [V]
- V_0 built-in potential [V]



Built-in potential



$$qV_0 = E_{Fn} - E_{Fp}$$

(built-in) Potential barrier for electrons and holes!

$$E_{Fn} = E_{Fi} + kT \ln\left(\frac{N_D}{n_i}\right)$$

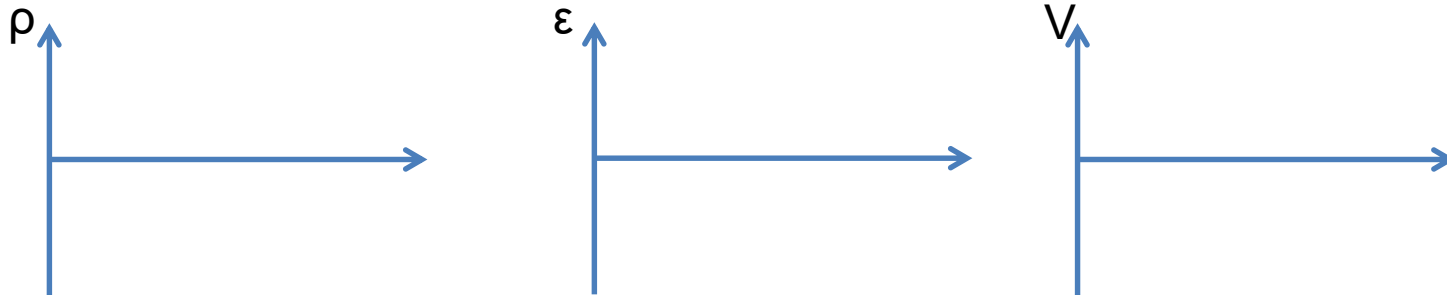
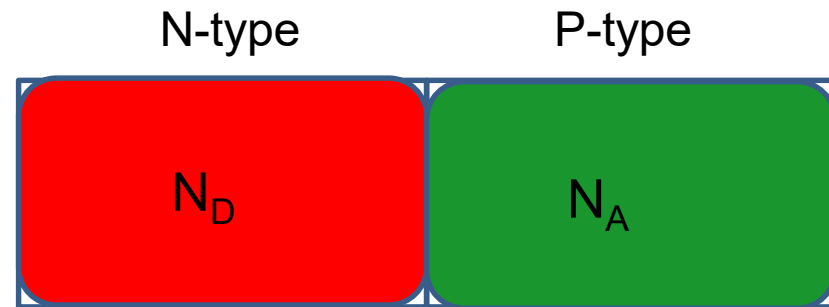
$$E_{Fp} = E_{Fi} - kT \ln\left(\frac{N_A}{n_i}\right)$$

$$qV_0 = kT \left[\ln\left(\frac{N_D}{n_i}\right) + \ln\left(\frac{N_A}{n_i}\right) \right] = kT \left[\ln\left(\frac{N_D N_A}{n_i^2}\right) \right]$$

homework: calculate depletion width for Si pn-junction with $N_D = N_A = 10^{17} \text{ cm}^{-3}$ at bias voltages $V=0 \text{ V}$ and $V= -1 \text{ V}$.

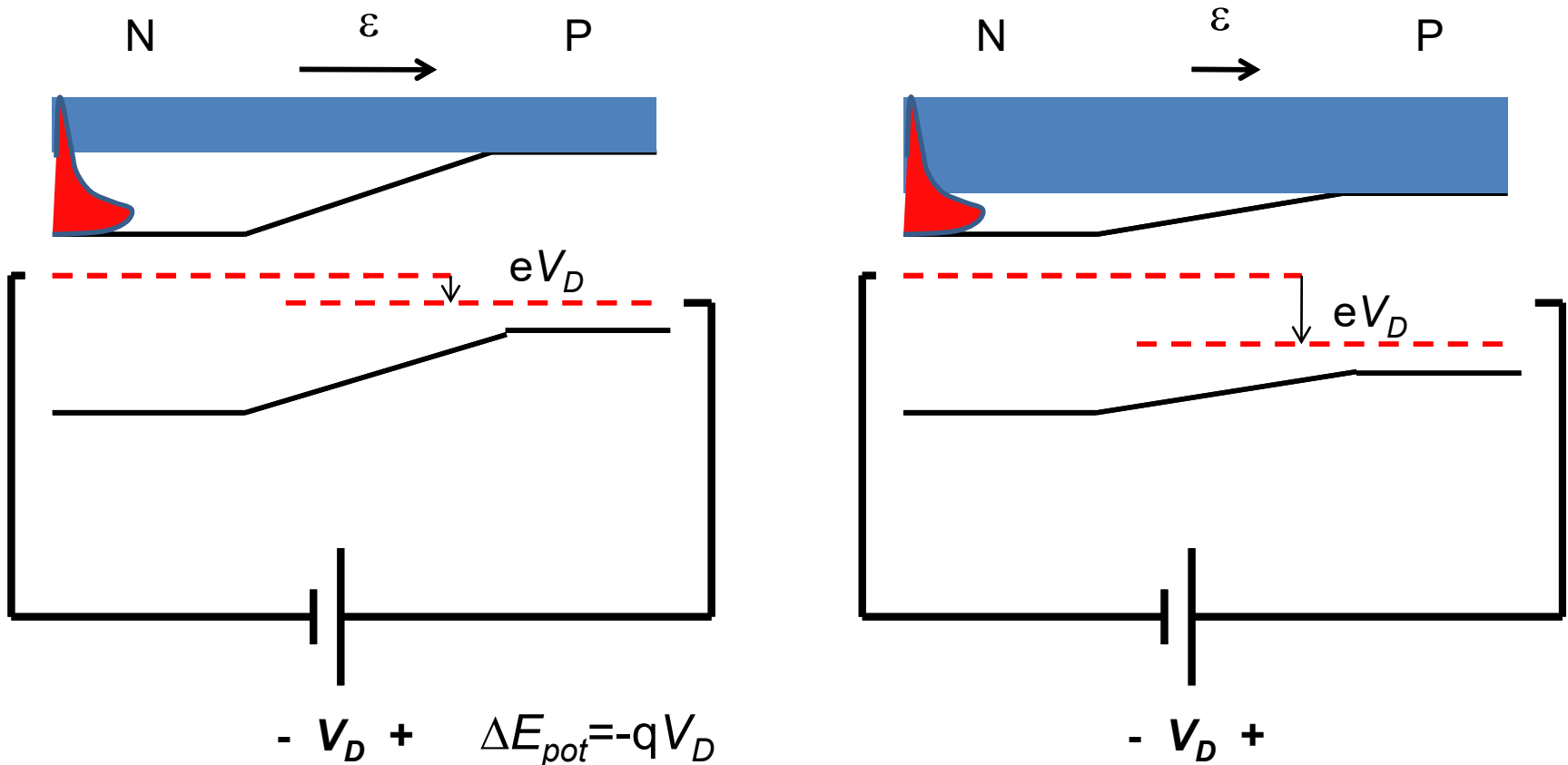
2 min exercise – asymmetric pn-junction

- Consider a pn-junction with $N_D = 5 * N_A$ (donors > acceptors)
- Sketch the
 - 1) charge distribution
 - 2) electric field
 - 3) potential

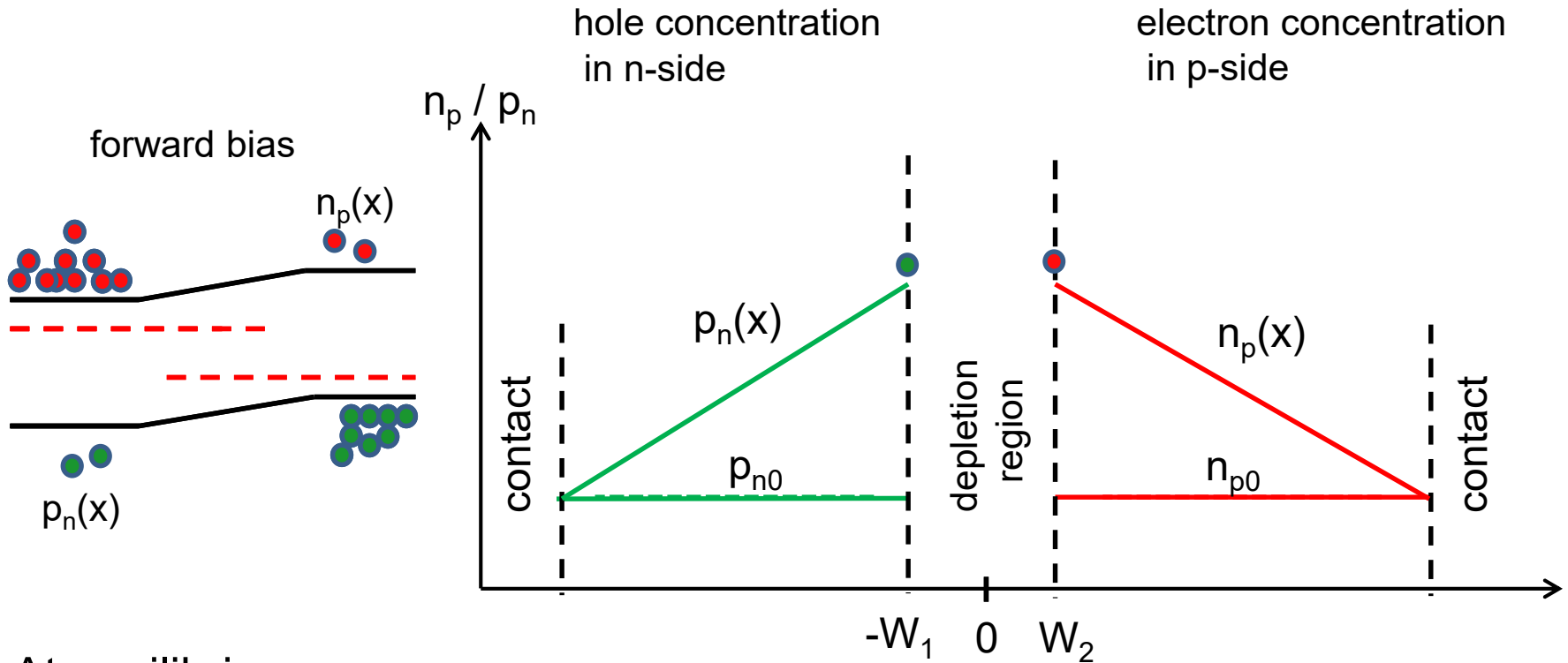


Diode – forward bias

- Only top of the electron distribution can pass over the barrier
- Increase bias \rightarrow exponentially increasing amount of electrons can pass
- Reduce electric field but counteracting built-in potential
- Depletion width is reduced



Minority carrier density at depletion edges at forward bias



At equilibrium:

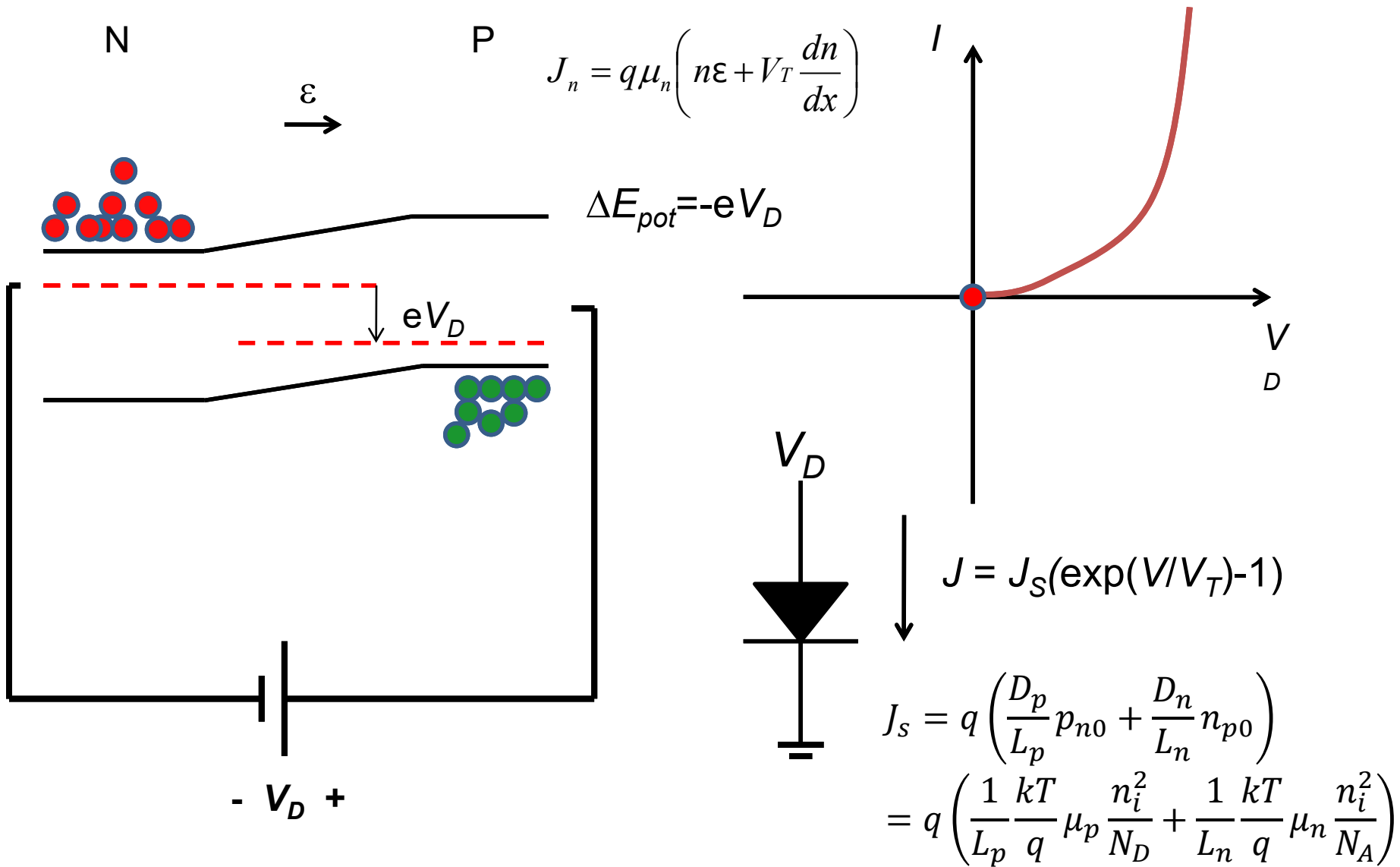
$$n_{p0} = n_i^2 / N_A$$

$$p_{n0} = n_i^2 / N_D$$

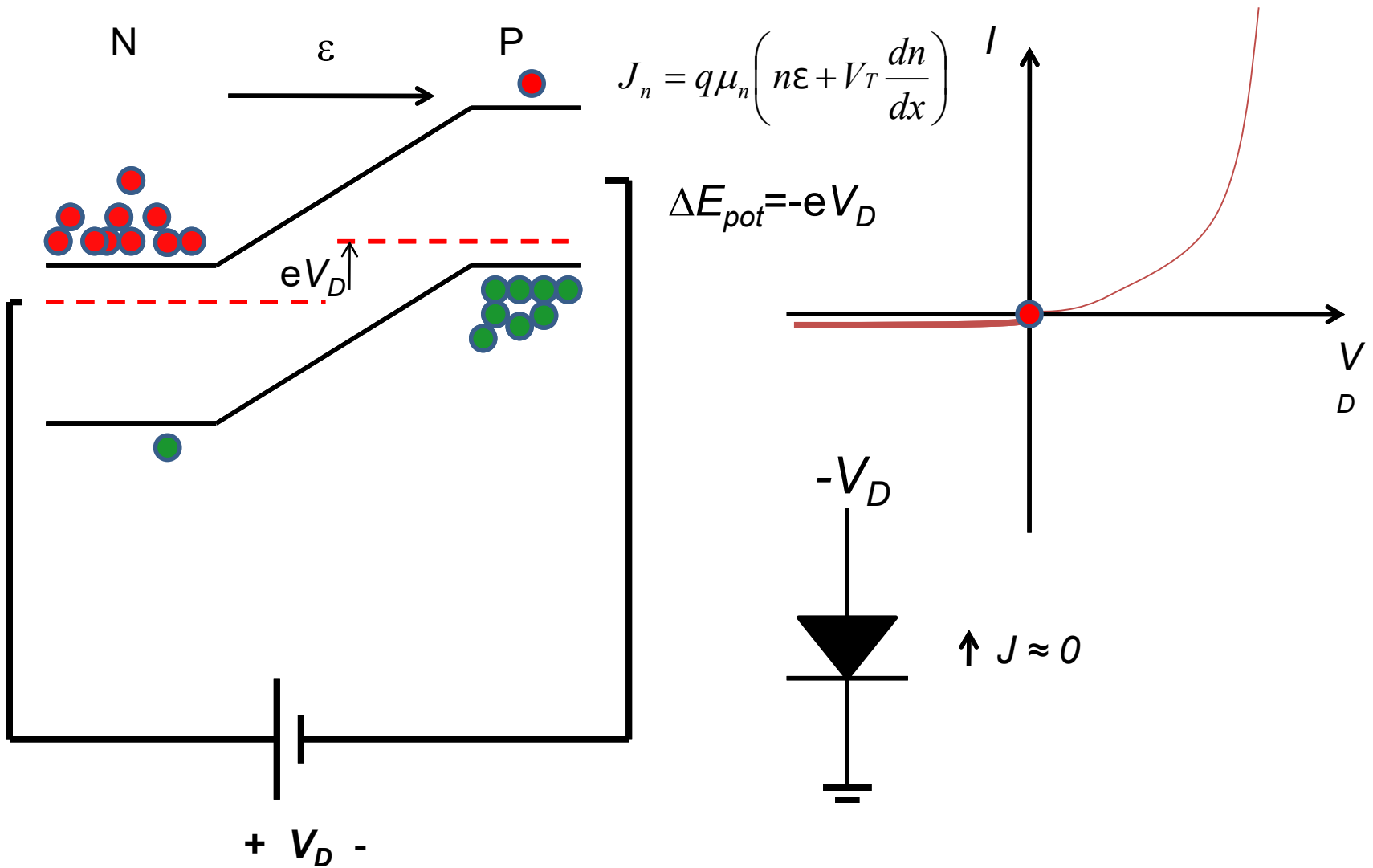
$$p_n(-W_1) = p_{n0} \exp\left(\frac{qV}{kT}\right)$$

$$n_p(W_2) = n_{p0} \exp\left(\frac{qV}{kT}\right)$$

Diode – forward bias



Diode – reverse bias



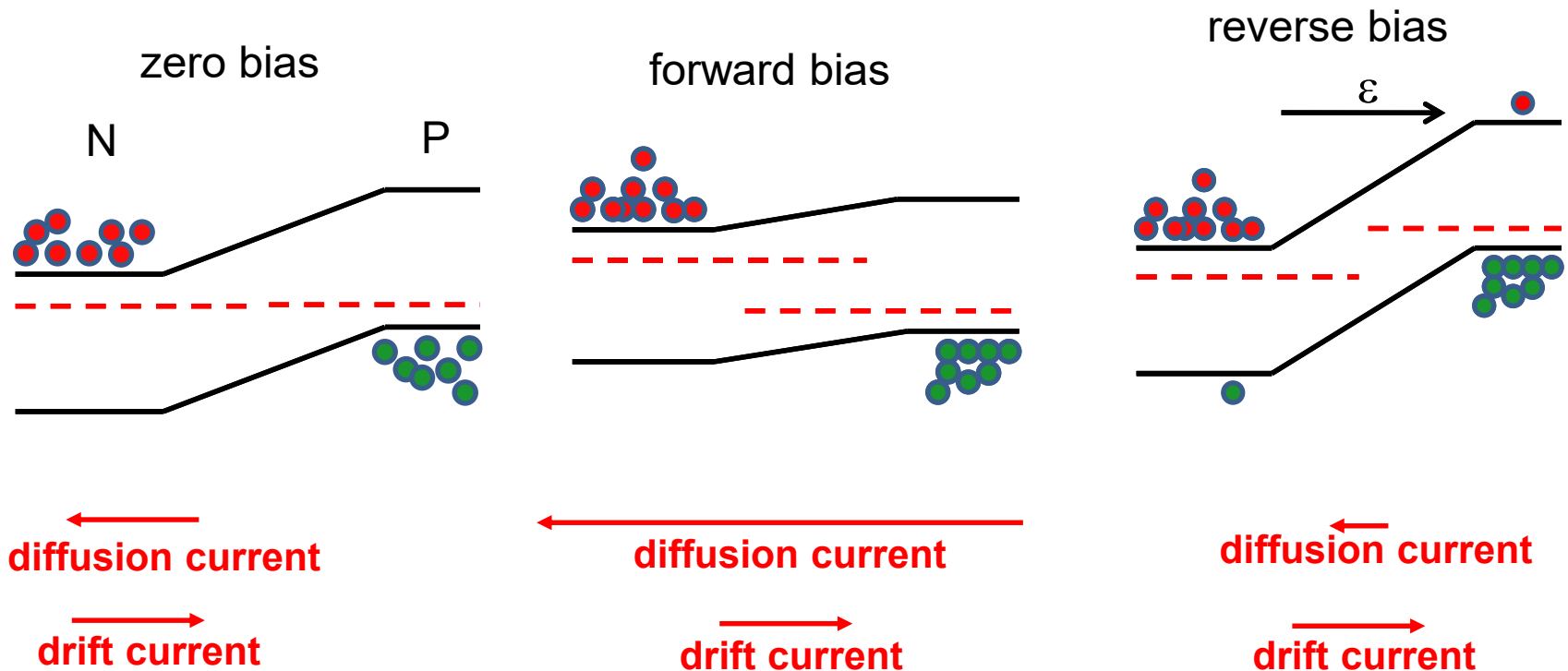
Diode – total current

$$J = J_s (e^{qV/nkT} - 1)$$

J_s = saturation current density
 n = ideality factor (1-2)

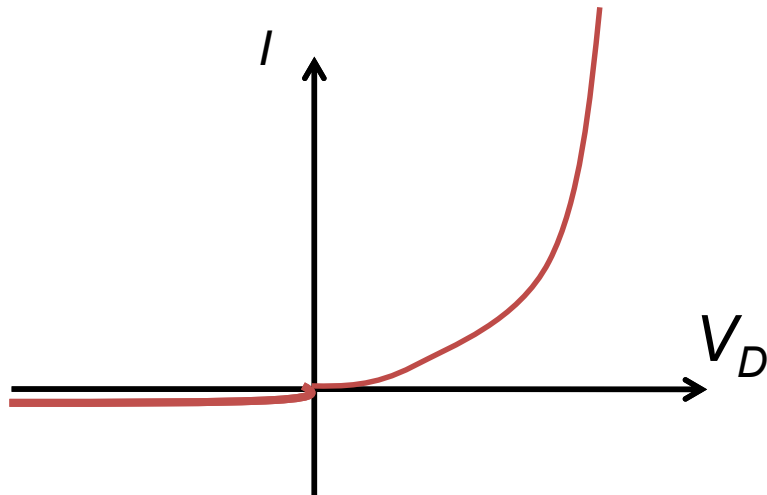
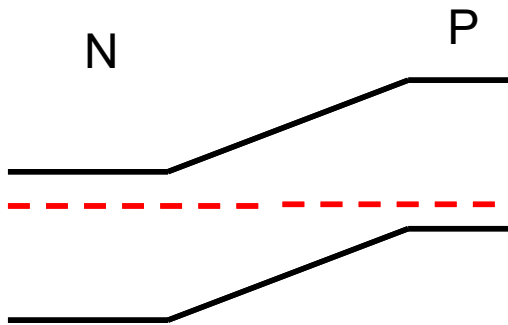
$$J_s = q \left(\frac{D_p}{L_p} p_{n0} + \frac{D_n}{L_n} n_{p0} \right)$$

$$= q \left(\frac{1}{L_p} \frac{kT}{q} \mu_p \frac{n_i^2}{N_D} + \frac{1}{L_n} \frac{kT}{q} \mu_n \frac{n_i^2}{N_A} \right)$$

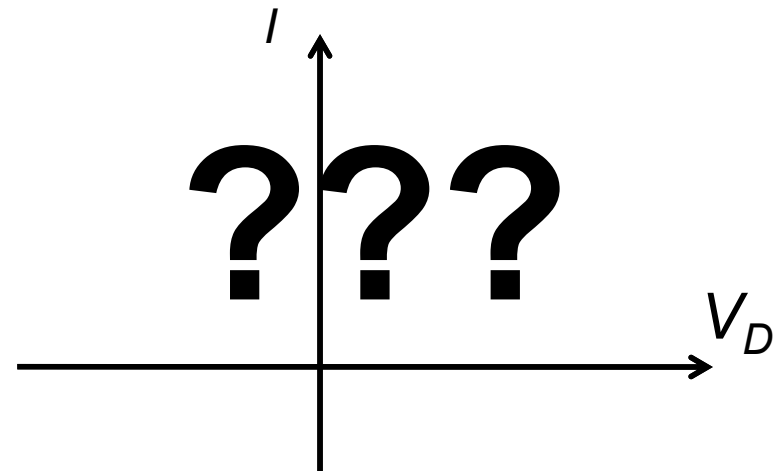
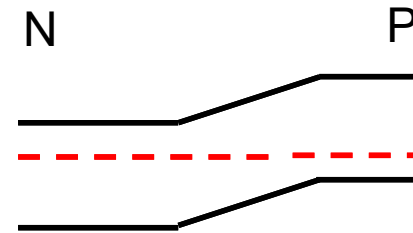


1 min exercise – Si vs Ge diode

Si ($E_g=1.11$ eV) pn-junction

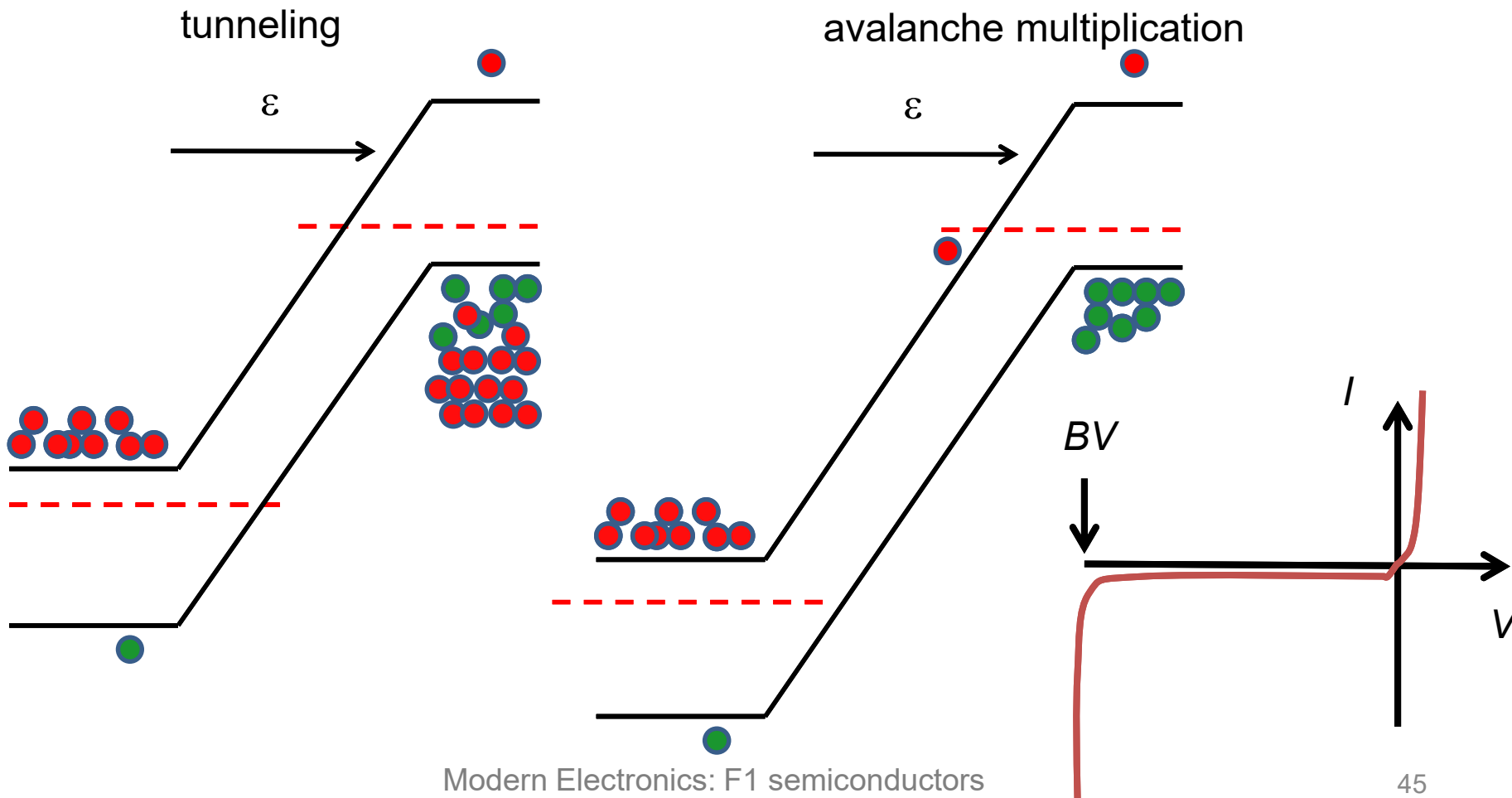


Ge ($E_g=0.67$ eV) pn-junction



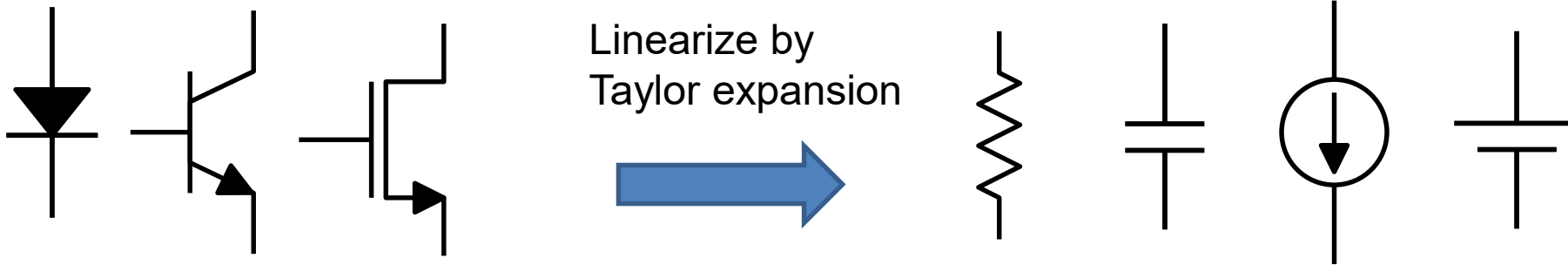
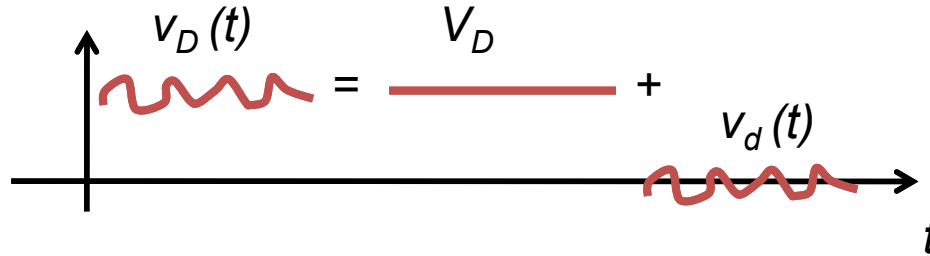
Zener tunneling / Avalanche Breakdown

- High reverse bias gives enough e-field to enable tunneling
- High energy of electron/hole can be lost by creating new e-h pairs through impact ionization



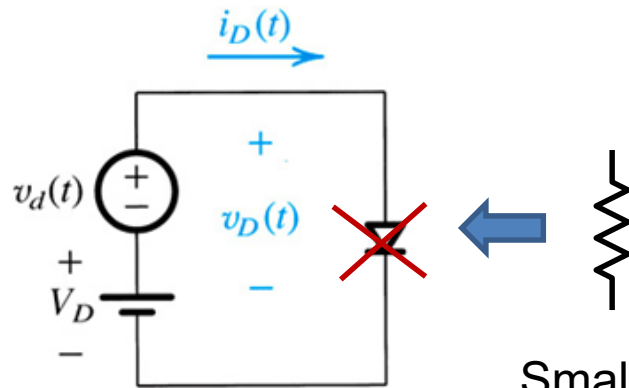
small-signal model

- Want to replace non-linear components with linear ones to simplify circuit calculations
- Constant V_D + small varying $v_d(t)$ = total voltage $v_D(t)$.

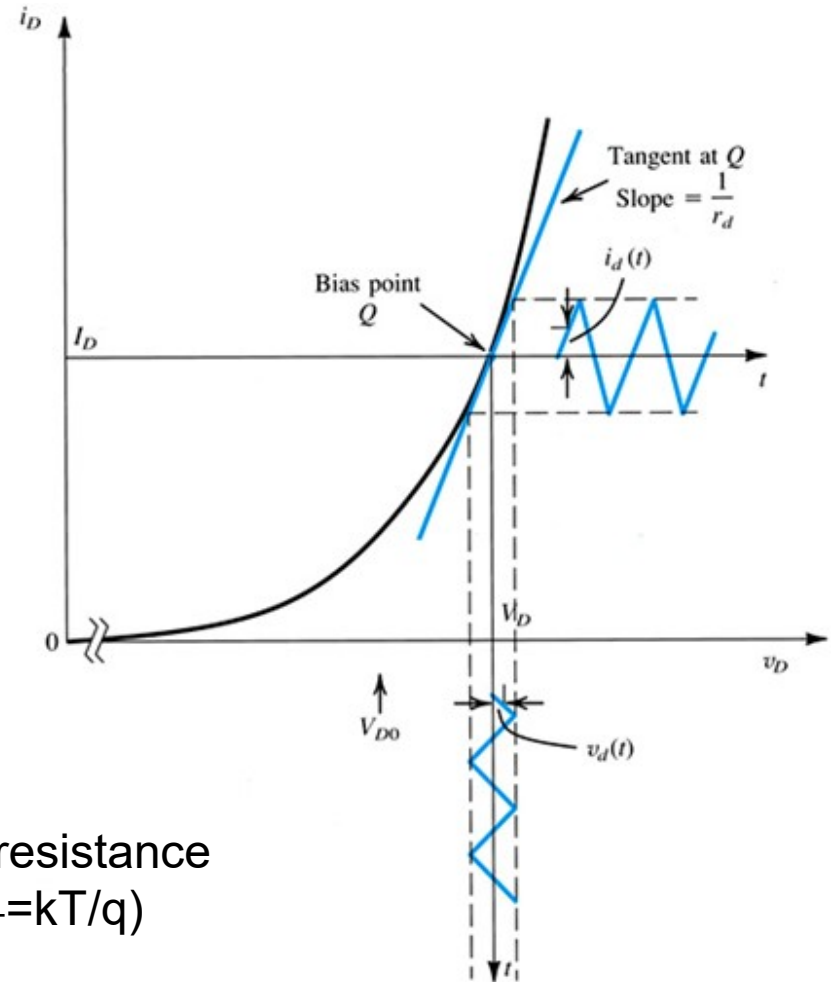


Small-signal model of diode (3.3.7)

- Diode IV is non-linear so difficult to do calculations
- Apply constant V_D and small varying $v_d(t)$
- Diode IV almost linear in a small region



Small signal resistance
 $r_d = V_T / I_D$ ($V_T = kT/q$)



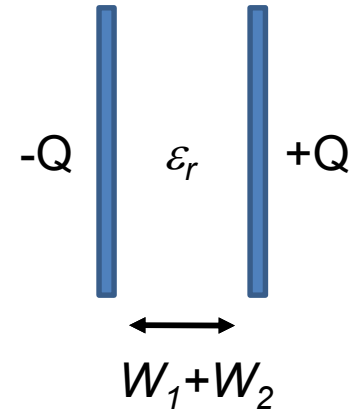
$$J = J_s (e^{qV_D/kT} - 1) \approx J_s e^{qV_D/kT}$$

depletion-region / junction capacitance

Definition: $C = \frac{Q}{V}$

$$C = \frac{\epsilon_r \epsilon_0}{W_1 + W_2} A$$

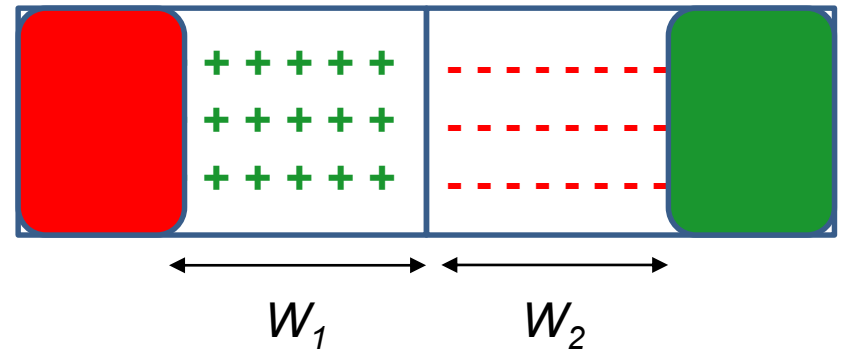
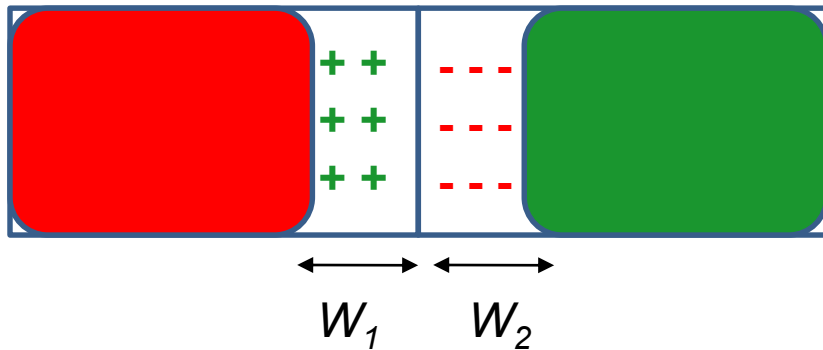
Example: parallel plate capacitor



$$Q_J = A \cdot q \cdot N_D (W_1 + W_2)$$

$$W \propto \sqrt{V_0 + V_R}$$

Non-linear relationship between V_R and $Q \rightarrow C(V_R)$



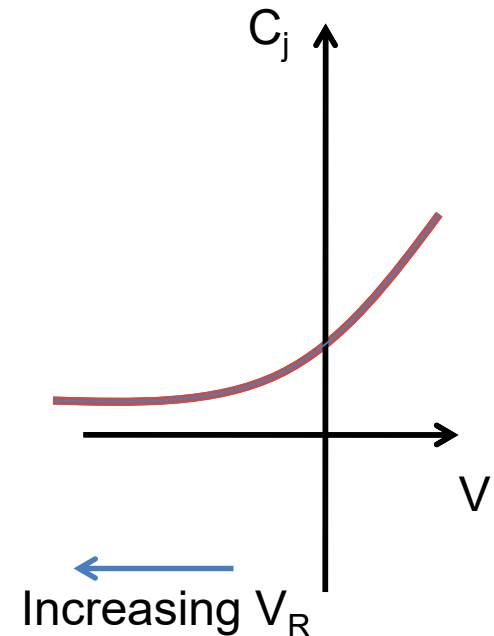
depletion region / junction capacitance

Definition $C_j = \frac{dQ_J}{dV_R}$ Applied bias (V_R) changes depletion width

Depletion width $W = \sqrt{\frac{2\epsilon_s}{q} \left(\frac{1}{N_A} + \frac{1}{N_D} \right) (V_0 + V_R)}$

Charge on either side $Q_J = AqN_DW_1 = Aq \frac{N_D N_A}{N_A + N_D} W$

$$C_J = A \sqrt{2\epsilon_s q \left(\frac{N_D N_A}{N_A + N_D} \right) \frac{1}{\sqrt{V_0 + V_R}}}$$

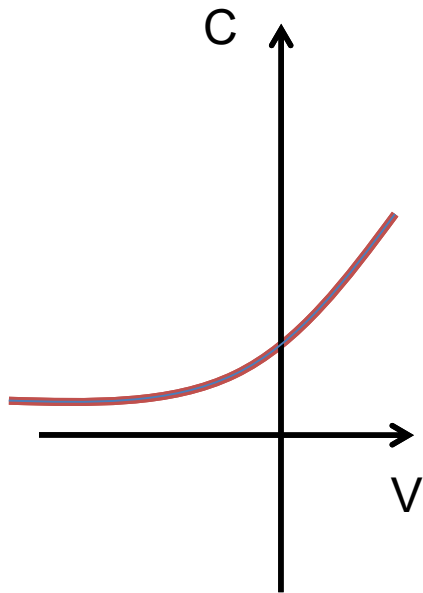


1 min exercise – pn-junction with forward bias

In forward bias there is a diffusion current flowing through the junction. How does the CV curve behave?

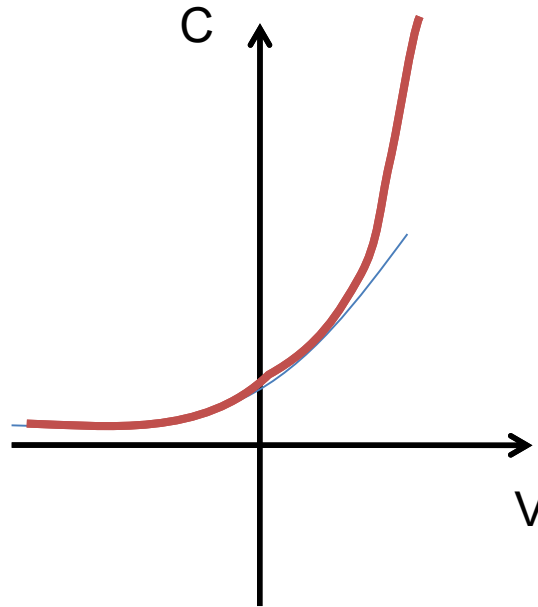
— Only C_j — $C = \frac{dQ}{dV}$

A



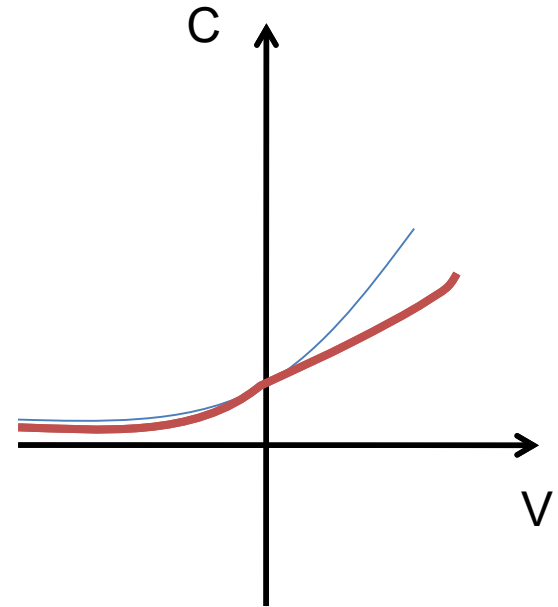
No change in capacitance

B



Larger capacitance for forward bias

C



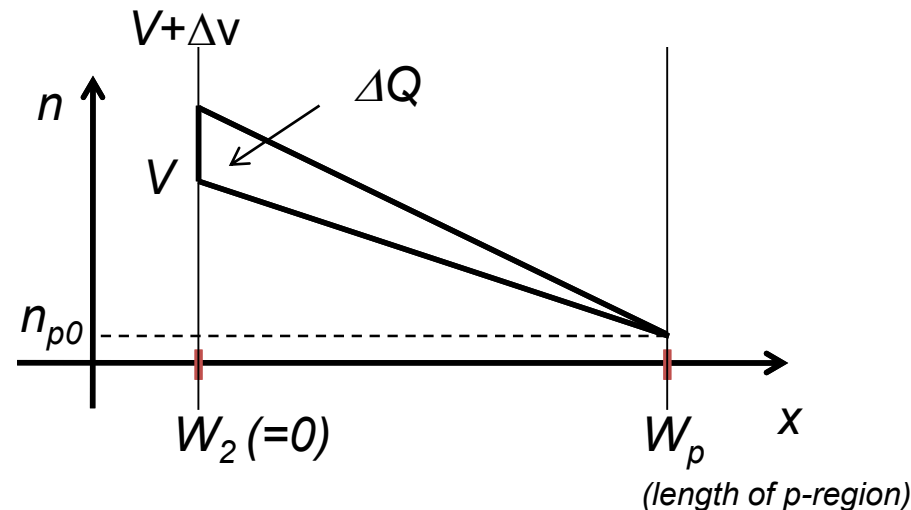
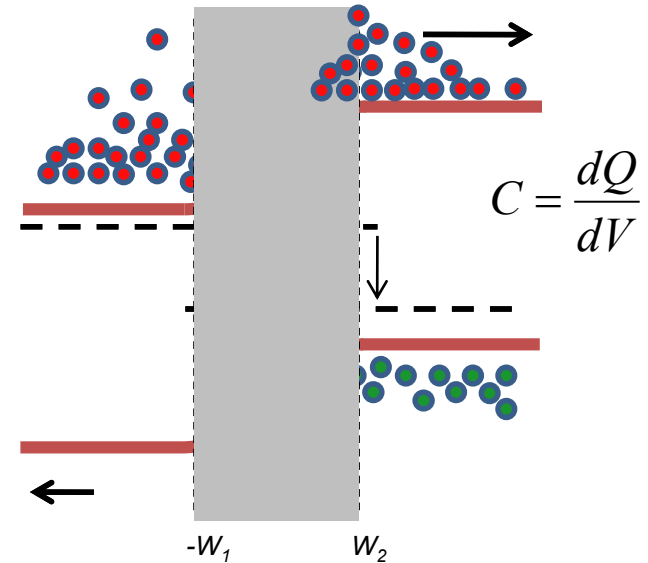
Lower capacitance for forward bias

diffusion capacitance

Forward bias \rightarrow inject minority carriers in neutral regions (electrons in p-region and holes in n-region) \rightarrow extra charge dQ .

$$n_p(W_2) = n_{p0} \exp\left(\frac{qV}{kT}\right)$$

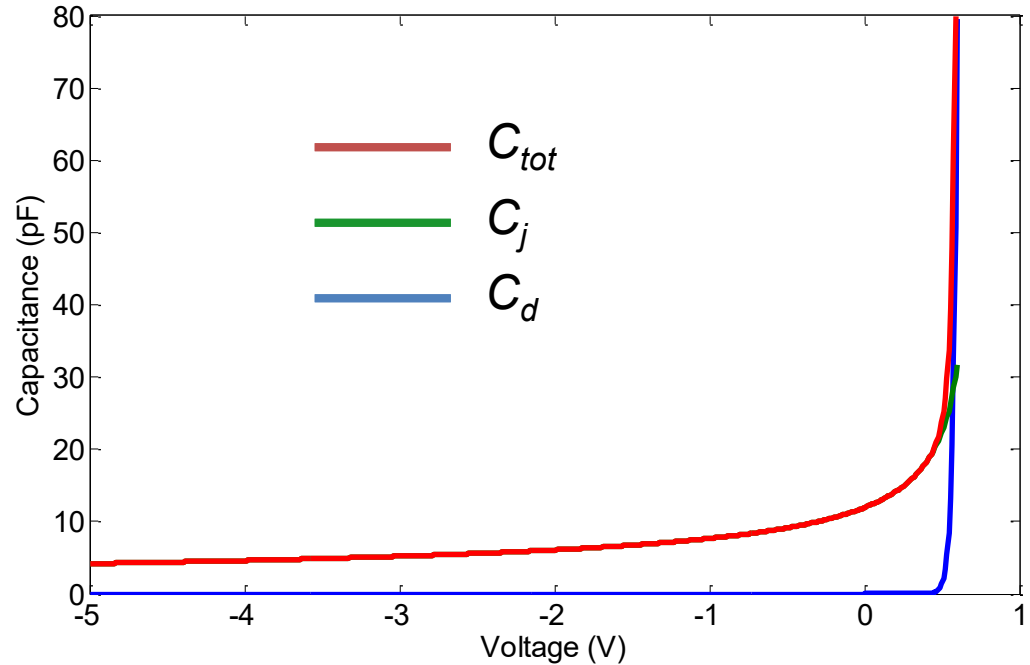
$$n_p(W_p) = n_{p0}$$



Total capacitance

$$C_{tot} = C_j + C_d$$

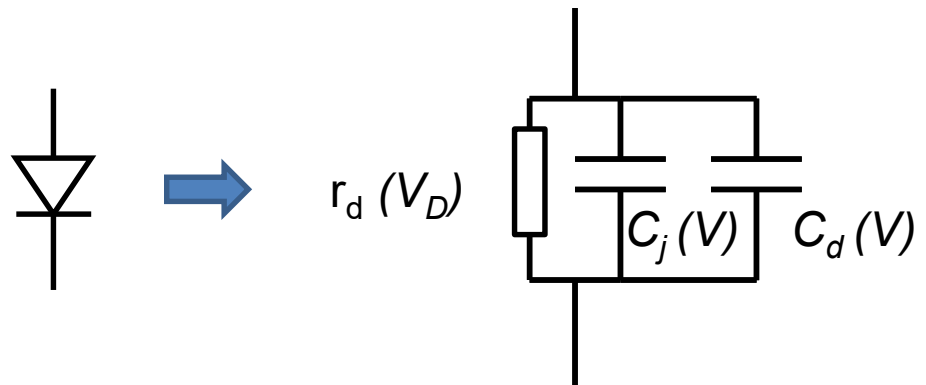
Add capacitances in parallel



C_j : dominates for reverse bias

C_{diff} : dominates for forward bias.

$C_{diff} \approx 0$ for reverse bias.



Summary – pn-junctions

- pn-junctions used in LEDs, solar cells, BJT, MOSFETs
- Poissons equations: charge distribution -> electric field -> potential
- Drift is balanced by diffusion in unbiased pn-junction
- Current given by ideal diode equation:
 - Forward bias: current (diffusion) increases exponentially
 - Reverse bias: current saturates
- Capacitances:
 - Junction capacitance due to change in depletion width (dominates reverse bias)
 - Diffusion capacitance due to change in charge in p/n region (dominates forward bias)
- Small-signal model (ok for $V \ll V_T$): replace diode with resistor + capacitances

$$J = J_s(e^{qV/nkT} - 1)$$